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WPINDEX	Derwent World Patents Index® Standard File
WPIX	Derwent World Patents Index® Subscriber File with Extension Abstract
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Subject Coverage	All patent-relevant areas of science and technology. The start of coverage varies by both subject matter and patent authority: <ul style="list-style-type: none"> • Pharmaceuticals: 1963 • Plastics and polymers: 1966 • Mechanical, electrical, and general technology: 1974 • Agricultural chemicals: 1965 • All other chemistry and general technology: 1970 		
File Type	Bibliographic		
Features	Thesauri European Patent Classification (/EPC), F-Term (/FTERM), FI-Term (/FCL), ICO (in-computer-only) Classification (/ICO), International Patent Classification (/IPC), Cooperative Patent Classification (/CPC), Manual Code (/MC), Polymer Indexing Enhanced (/PLE), Title Terms (/TT), and US National Patent Classification (/NCL). There is a thesaurus-like feature in the Compound Number (/DCN), Registry Number (/DRN), Patent Assignee Code (/PACO), and Plasdoc Key Serials (/KS)		
	Alerts (SDIs)	Monthly, weekly, or with each update (2 updates per week) (every update is the default)	
	CAS Registry Number® Identifiers	<input type="checkbox"/>	SLART <input checked="" type="checkbox"/>
	Keep & Share	<input checked="" type="checkbox"/>	Structures <input type="checkbox"/>
Record Content	Bibliographic Records <ul style="list-style-type: none"> • Patent family data available for each bibliographic record (Derwent patent family): <ul style="list-style-type: none"> - Basic patent - Equivalents (information about the same invention issued in other countries) • Invention Level: bibliographic data and Derwent value-added titles, abstracts, general and (where appropriate) in-depth chemical and electrical indexing. Electrical, engineering drawings and chemical structure drawings. Data from the individual member patents is collated and de-duplicated. • Member Patent Level (Publication Level): bibliographic data, equivalent abstracts and general indexing information associated with individual documents in the patent family. Additional first-level elements comprise author titles and abstracts, claims, original inventor, patent assignee and agent information including addresses. • Claims information is available for more than 20 patent authorities. • The Derwent Patents Citation® Index is fully integrated in DWPI, covering backward and forward patent citations, as well as literature citations of 32 patent authorities. • Certain features are restricted to eligible users holding an appropriate subscription. WPIDS users with the appropriate level of subscription are entitled to search for special indexing like chemical, polymer coding, or chemical manual codes. WPIX subscribers can also access display of abstract extensions, and documentation abstracts. • Numeric values of 59 physical and chemical properties in more than 20,000 unit variants are searchable in all English text fields (titles, abstracts, claims). 		

File Size	<ul style="list-style-type: none"> More than 58 million records with more than 46 million images (02/2023) 																																																														
Coverage	<ul style="list-style-type: none"> 1963-present Electrical and engineering drawings: 1988-present Chemical structure drawings 1988-present 																																																														
Updates	Updated twice a week with about 47,000 new records (Basic Patents), about 66,000 Equivalents, Polymer and Chemical Coding, and about 43,000 images (technical drawings and chemical structure drawings)																																																														
Language	English																																																														
Database Producer	Clarivate Friars House 160 Blackfriars Rd. London SE1 8EZ United Kingdom																																																														
	Copyright Holder: Clarivate																																																														
Sources	<p>Patent documents are covered from 59 patent authorities:</p> <table> <tbody> <tr><td>Argentina (1975)</td><td>Kazakhstan (2002-present)</td></tr> <tr><td>Armenia (2002-present)</td><td>Kyrgyzstan (2002-present)</td></tr> <tr><td>Australia (1963-69,1983-pres.)</td><td>Luxembourg (1984-present)</td></tr> <tr><td>Austria (1975-present)</td><td>Malaysia (2005-present)</td></tr> <tr><td>Belarus (2002-present)</td><td>Mexico (1997-present)</td></tr> <tr><td>Belgium (1963-present)</td><td>Moldova (2002-present)</td></tr> <tr><td>Brazil (1976-present)</td><td>Netherlands (1963-present)</td></tr> <tr><td>Canada (1963-present)</td><td>New Zealand (1993-present)</td></tr> <tr><td>China (1987-present)</td><td>Norway (1974-present)</td></tr> <tr><td>Czech Republic (1994-present)</td><td>PCT (WIPO) (1978-present)</td></tr> <tr><td>Czechoslovakia (1975-1994)</td><td>Philippines (1994-present)</td></tr> <tr><td>Denmark (1974-present)</td><td>Poland (2011-present)</td></tr> <tr><td>Eurasian Patent Organization (2002-present)</td><td>Portugal (1974-present)</td></tr> <tr><td>European Patent Office (1978-present)</td><td>Rep. of Korea (1986-present)</td></tr> <tr><td>Finland (1974-present)</td><td>Romania (1975-present)</td></tr> <tr><td>France (1963-present)</td><td>Russian Federation (1994-present)</td></tr> <tr><td>Georgia (2002-present)</td><td>Singapore (1995-present)</td></tr> <tr><td>Germany (1963-present)</td><td>Slovakia (1994-present)</td></tr> <tr><td>Germany (Utility Models) (1995-present)</td><td>South Africa (1963-present)</td></tr> <tr><td>German (Dem. Rep.) (1963-1990)</td><td>Soviet Union (1963-1994)</td></tr> <tr><td>Gulf Cooperation Council (2011-present)</td><td>Spain (1983-present)</td></tr> <tr><td>Hong Kong (2011-present)</td><td>Sweden (1974-present)</td></tr> <tr><td>Hungary (1975-present)</td><td>Switzerland (1963-present)</td></tr> <tr><td>India (2004-present)</td><td>Taiwan (1993-present)</td></tr> <tr><td>Indonesia (2010-present)</td><td>Tajikistan (2002-present)</td></tr> <tr><td>Ireland (1963-69,1995-pres.)</td><td>Thailand (2010-present)</td></tr> <tr><td>Israel (1975-present)</td><td>Turkey (2015-present)</td></tr> <tr><td>Italy (1966-69,1978-present)</td><td>United Kingdom (1963-present)</td></tr> <tr><td>Japan (1963-present)</td><td>United States (1963-present)</td></tr> <tr><td></td><td>Uzbekistan (2002-present)</td></tr> <tr><td></td><td>Vietnam (2010-present)</td></tr> </tbody> </table> <p>Additional Sources are:</p> <ul style="list-style-type: none"> - Research Disclosure (1978-present) - International Technology Disclosures (1984-93) 	Argentina (1975)	Kazakhstan (2002-present)	Armenia (2002-present)	Kyrgyzstan (2002-present)	Australia (1963-69,1983-pres.)	Luxembourg (1984-present)	Austria (1975-present)	Malaysia (2005-present)	Belarus (2002-present)	Mexico (1997-present)	Belgium (1963-present)	Moldova (2002-present)	Brazil (1976-present)	Netherlands (1963-present)	Canada (1963-present)	New Zealand (1993-present)	China (1987-present)	Norway (1974-present)	Czech Republic (1994-present)	PCT (WIPO) (1978-present)	Czechoslovakia (1975-1994)	Philippines (1994-present)	Denmark (1974-present)	Poland (2011-present)	Eurasian Patent Organization (2002-present)	Portugal (1974-present)	European Patent Office (1978-present)	Rep. of Korea (1986-present)	Finland (1974-present)	Romania (1975-present)	France (1963-present)	Russian Federation (1994-present)	Georgia (2002-present)	Singapore (1995-present)	Germany (1963-present)	Slovakia (1994-present)	Germany (Utility Models) (1995-present)	South Africa (1963-present)	German (Dem. Rep.) (1963-1990)	Soviet Union (1963-1994)	Gulf Cooperation Council (2011-present)	Spain (1983-present)	Hong Kong (2011-present)	Sweden (1974-present)	Hungary (1975-present)	Switzerland (1963-present)	India (2004-present)	Taiwan (1993-present)	Indonesia (2010-present)	Tajikistan (2002-present)	Ireland (1963-69,1995-pres.)	Thailand (2010-present)	Israel (1975-present)	Turkey (2015-present)	Italy (1966-69,1978-present)	United Kingdom (1963-present)	Japan (1963-present)	United States (1963-present)		Uzbekistan (2002-present)		Vietnam (2010-present)
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**Sources
(cont.)**

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Cluster

- | | |
|--|--|
| <ul style="list-style-type: none"> • AEROTECH • ALLBIB • AUTHORS • BIOSCIENCE • CORPSOURCE • ENGINEERING | <ul style="list-style-type: none"> • FORMULATIONS • HPATENTS • NPS • PATENTS • POLYMERS |
|--|--|

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**Related
Databases**

- DWPI – Derwent Markush structure database includes all generic compounds which have been indexed in the corresponding DWPI database
- DCR – Derwent Chemistry Resource structure database includes specific compounds which have been indexed in the corresponding DWPI database

DWPI Invention Level**Search Fields**

Fields that allow left truncation are indicated by an asterisk (*).

Search Field Name	Search Code	Search Examples	Display Codes
Basic Index* (contains single words from AB, ABDT, ABEQ, ABEX, ACTN, ACTV, ADV, ALE, DETD, DRWD, NOV, TECH, TI, TT, UADV, and USE) (18)	None or /BI (or /BIX)	S DRILLING FLUID AND EMULS? S ?PHENYLETHER? S #####DIPHENYLETHER S ULCER TREATMENT(L)ORAL	AB, ABDT, ABEQ, ABEX, ACTN, ACTV, ADV, ALE, DETD, DRWD, NOV, TECH, TI, TT, UADV, USE
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DWPI Invention Level

Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
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Abstract, Documentation Type, Preparation *(1,18)	/ABDT.PRP	S IMIDAZOL?/ABDT.PRP	ABDT
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Accession Number Week, Supplement	/DW.AN	S 197022/DW.AN	AN
Activity *(18)	/ACTV	S ANTIBIOTIC ACTIVITY/ACTV	AB, ACTV
Advantage *(18)	/ADV	S LASER BEAM?/ADV	AB, ADV
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Application Country, Basic	/AC.B	S AU/AC.B	HITMEMB
Application Date (3,4)	/AD	S JAN 1993-APR 1993/AD(P)FR/AC	ADT, AI
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Application Number (3,5)	/AP	S GB1989-219641/AP	ADT, AI
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Application Number, Year (4)	/AP.YR	S 2004/AP.YR	ADT, AI
Application Type	/APT	S RELATED TO/APT	ADT, AI
Application Year (3,4)	/AY	S 1990-1991/AY	ADT, AI
Application Year, Basic (3,4)	/AY.B	S 2017-2020/AY.B	HITMEMB
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Cooperative Patent Classification	/CPC	S D03D0015-0011/CPC	CPC
Country Count (4)	/CYC	S 20-30/CYC	CYC
CPC, Action Date (4)	/CPC.ACD	S 20130101/CPC.ACD	CPC.TAB
CPC, Codes of a Combination Set	/CPC.CS	S A61K0039-42/CPC.CS	CPC, CPC.TAB
CPC, Keyword Terms	/CPC.KW	S INVENTION/CPC.KW	CPC.TAB
CPC, Version	/CPC.VER	S 20130101/CPC.VER	CPC.TAB
Cross Reference	/CR (or /XR)	S 1990-001459/CR S 1990-001459/AN,CR	CR
Crossover Accession Number	/ANX	S 1980-B7362C/ANX	ANX

DWPI Invention Level

Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
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Document Level	/DLVL		not displayed
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Document Number Non CPI	/DNN	S N1983-041955/DNN	DNN, DN
Document Type	/DT	S L7 AND P/DT	not displayed
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DWPI Registry Number (22)	/DRN	S DRN-0001/DRN S 0001/DRN	DRN
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DWPI Update, Basic (formerly Derwent Week, Basic) (4,6)	/DW.B	S 199315/DW.B(P)US/PC.B	PI, PI.B
Entry Date (4)	/ED	S ED>19940201 AND L10	ED
European Patent Classification (8)	/EPC (or /ECLA, or /EPCLA)	S A01B0015-20/EPC	EPC
Field Availability	/FA	S L7 NOT NOAB/FA S L11 AND GI/FA	FA
File Segment	/FS	S PLASMA AND EPI/FS	FS
Filing Details (5,6)	/FDT	S US5072794/FDT S EP105613/FDT	FDT
Filing Details, Patent Country (WIPO code and text)	/FDT.PC (or /RLPC)	S CANADA/FDT.PC	FDT
Filing Details, Patent Kind	/FDT.PK (or /RLPK)	S CA/FDT.PK	FDT
Filing Details, Patent Number	/FDT.PN (or /RLPN)	S CA1248729/FDT.PN	FDT
Filing Details, Type	/FDT.TP	S REISSUE OF/FDT.TP	FDT
Fragmentation Code (PLASDOC) (19, 20, 22)	/FG (or /AM)	S (012(P)032(P)046)/FG	FG, PLC
ICO (in-computer-only) Classification (8)	/ICO	S K61M/ICO	ICO
Index Term	/IT (or /KW)	S DCR-168/IT S 168/IT	IT
International Patent Classification (all versions (1-8): ICA, ICI, ICM, ICS, IPC.REF) (8)	/IPC	S C12P0021-08/IPC S C12P0021/IPC S C12P/IPC	IPC
Inventor	/IN (or /AU)	S HALE, A H/IN S HALE A H/IN,PA	IN
IPC, Action Date (4)	/IPC.ACD	S IPC.ACD>20070107	IPC.TAB
IPC, Additional (supplementary, IPC 1-7))	/ICA	S A01K067-027/ICA	ICA
IPC, First	/IPC.F	S A61K0008-63/IPC.F	HIT, IPC.TAB
IPC, Index (complementary, IPC 1-7)	/ICI	S B03D0103:04/ICI	ICI

DWPI Invention Level**Search Fields (cont'd)**

Search Field Name	Search Code	Search Examples	Display Codes
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IPC, Reform	/IPC.REF	S A01B0003-44/IPC.REF	IPCI, IPCR, IPC
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IPC, Version (4)	/IPC.VER	S 20080101/IPC.VER	IPC.TAB
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Japanese Patent Classification (FI-Terms)	/FCL	S C12N0001-00 A/FCL	FCL
Japanese Patent Classification (FI-Terms, additional)	/FACL	S A23L0033-135/FCL(T)ZNA/FCL	FCL
Japanese Patent Classification (FI-Terms, index)	/FICL	S A01B0069-00 303 Z/FACL	FCL
Japanese Patent Classification (FI-Terms, main)	/FMCL	S A61K0035-12/FICL	FCL
Japanese Patent Classification (F-terms) (8)	/FTRM (or /FTERM, or /FTCLA, or /JPCLA)	S H01B0001-02/FMCL	FCL
Language (ISO code and text)	/LA	S 5B001/AA01/FTRM S (4F100(T)DC11)/FTRM S FR/LA(P)EP/PC AND L3 S FRENCH/LA(P)EP/PC(P)1990/PY	PI
Manual Code (8,9,23)	/MC	S A12-W10A/MC	MC
Markush Compound Number	/MCN	S 0153-12201-CL/MCN	MCN, CMC
Mechanism of Action *	/ACTN	S KINASE INHIBITOR?/ACTN	AB, ACTN
Novelty* (11,18)	/NOV	S EXCITATION LIGHT/NOV	NOV
Number of Drawings (4)	/DRWN	S DRWN=9	DRWN
Number of Pages (4)	/PGN	S PGN=5 AND L2	PI
Patent Assignee (10)	/PA (or /CS)	S SHELL OIL/PA S "NEW YORK WIRE"?/PA	PA
Patent Assignee Code (8,12)	/PACO	S SHEL/PACO	PA
Patent Country (6,13)	/PC	S GB/PC(P)1989/AY S UNITED KINGDOM/PC	PI
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Patent Number (5,6)	/PN	S US5198416/PN S EP100323/PN S US20060000001/PN S US,100,503/PN S WO99/9/PN S JP6905629B/PN	PI, PN
Patent Number, Basic (5,6)	/PN.B	S US5198416/PN.B	PI
Patent Number Count (4)	/PNC	S 5-10/PNC	PNC
Patent Number/Kind Code	/PNK	S WO2009006253A2/PNK	PNK
Patent Number/Kind Code, Basic	/PNK.B	S TH43458A/PNK.B	PNK.B
Patent Publication Type	/PT	S EQUIVALENT/PT AND BE/PC	PI, PN
Plasdoc Key Serials (19,20,21,22)	/KS	S 0004 0003/KS	KS, PLC
Polymer Indexing Enhanced (21,22)	/PLE	S (R01737(P)C088)/PLE	PLE

DWPI Invention Level**Search Fields (cont'd)**

Search Field Name	Search Code	Search Examples	Display Codes
Priority Country (15)	/PRC	S FR/PRC S GB/PRC(P)1990/PRY	PRAI
Priority Country, First Priority Date (4,15)	/PRCF /PRD	S AU/PRCF S 19880930/PRD S JUNE 1991/PRD(P)FR/PRC	PRAI PRAI
Priority Date, First (4,15)	/PRDF	S JUNE 1991/PRDF	PRAI
Priority Number (5,15)	/PRN	S 1988US-000252206/PRN S US1988-252206/PRN S 1990DE-0000010670/PRN S DE1990-10670/PRN	PRAI
Priority Number, First	/PRNF	S AL1961-8036/PRNF	PRAI
Priority Number, Year (4)	/PRN.YR	S 2005/PRN.YR	PRAI
Priority Year (4,15)	/PRY	S 1990-1991/PRY(P)NL/PRC	PRAI
Priority Year, First (4,15)	/PRYF	S 1992/PRYF	PRAI
Publication Date (4,6)	/PD	S 19900404/PD	PI
Publication Date, Basic (4,6)	/PD.B	S 1 APR 1990-15 APR 1990/PD(P)GB/PC	PI
Publication Year (4,6)	/PY	S 19930330/PD.B(P)US/PC.B	PI
Publication Year, Basic (4,6)	/PY.B	S 1990/PY.B(P)JP/PC.B	PI
Ring Index Number (22)	/RIN	S RIN-00012/RIN S 00012/RIN	RIN, CMC
Ring Index Number, Unlinked (22)	/RINU	S 00044/RINU S RIN-00044/RINU	RINU, RIN, CMC
Role (20)	/RL	S DCR-1/DCR(T)(P OR PRD)/RL	IT, CMC
Technology* (11,18)	/TECH	S DYEING AGENT#/TECH,BI	TECH
Title* (18)	/TI	S DRILLING FLUID#/TI	TI
Title Terms * (16,18) (incl. Additional Words)	/TT	S DRILL/TT S FIBRE-OPTIC/TT	TT
Update Date (4)	/UP	S JAN 2007/UP	UP
Update Date Abstract (4)	/UPAB	S FEB 2009/UPAB	UPA
Update Date Chemical Code (4,22)	/UPB	S UPB=APR 2005	UPB
Update Date Cooperative Patent Classification	/UPCP	S JAN 2021-JUNE 2021/UPCP	UPCP
Update Date Enhanced Title (4)	/UPTI	S 20050422/UPTI AND L2	UPTI
Update Date Index Term (4)	/UPIT (or /UPKW)	S 20050412/UPIT	UPIT
Update Date International Patent Classification (4)	/UPIC	S 20090918/UPIC	UPIC
Update Date Inventor (4)	/UPIN	S UPIN=3 MAY 2013	UPIN
Update Date Japanese Patent Classification (4)	/UPFT	S UPFT>20210601	UPFT
Update Date Manual Code (4)	/UPMC	S 2021/UPMC	UPMC
Update Date Patent Assignee (4,22)	/UPPA	S 20050426/UPPA AND L15	UPPA
Update Date Patent Family (4)	/UPP	S FEB 1994-APR 1994/UPP	UPP
Update Date Polymer Indexing (4)	/UPA	S UPA=APR 2005	UPA
US National Patent Classification, Current (8)	/NCL	S 002006100/NCL	NCL
US National Patent Classification, Current (main)	/NCLM	S 002/NCLM	NCL
US National Patent Classification, Current (secondary)	/NCLS	S 004/NCLS	NCL
Use Section* (18)	/USE	S (SYNTHESIS AND BIOSYNTHETIC)/ USE S ?PHENYLETHER?/USE S ?TREATMENT?/UADV	USE
Use/Advantage Section * (18)	/UADV	S ?TREATMENT?/UADV	UADV

- (1) This field is displayable in WPIX only. Available for 1995-1999.
- (2) This field is displayable in WPIX only. Available from update 199908 onwards.
- (3) Application Information is linked by (P) proximity to the patent information of the respective document.
- (4) Numeric search field that may be searched using numeric operators or ranges.
- (5) Numbers are searchable in DWPI and STN format.
- (6) Patent information (PN, PC, PK only) and application information of one patent document is linked by (P) proximity.
- (7) The classification text of DWPI classes is available in abbreviated form for EXPAND, however not for SEARCH
- (8) A thesaurus is available in this field.
- (9) DWPI manual codes automatically echo each search term and its definition when you search.
- (10) Search with implied (S) proximity is available in this field. Bound phrases have to be searched with quotation marks.
- (11) Available from Update 199908 onwards.
- (12) The list of Clarivate (UK) Limited-assigned company codes for patent assignees matched with company names is available in this field. See page 18.
- (13) Enter HELP COUNTRY online for detailed coverage information.
- (14) Enter HELP KIND online for definitions of the patent document kind codes.
- (15) Priority information referring to the same application is linked by (P) proximity.
- (16) RL includes roles for DCR-, MCN-, DRN- and DCN-numbers, search numbers and roles with (T)-proximity
- (17) A function for preferred and forbidden terms (USE, UF relationship) is available for EXPAND and SEARCH in this field – see 'DWPI Title Terms' on page 18. By default, the preferred term is searched, when a forbidden one is part of the query.
- (18) The words AND, IS, OF, THE, and TO are not indexed in this field.
You may use these stop words in your search statement, however at their position a (1W)-proximity is used by the system.
- (19) Search with implied (P) proximity is available in this field.
- (20) Fields /FG and /KS were discontinued as of DWPI update 199401 being replaced by field /PLE.
- (21) /PLE is available since DWPI update 199332, replacing fields /FG and /KS. There are three levels of linking in this field: tightest – (S), middle – (P), widest – (L) proximity. The Polymer Indexing Thesaurus is available online in /PL.
- (22) Field available in subscriber files WPIDS/WPIX only.
- (23) Manual codes of sections A-N are available in the subscriber files WPIDS/WPIX only.

Super Search Fields

Enter a super search code to execute a search in one or more fields that may contain the desired information. Super search fields facilitate crossfile and multifile searching. EXPAND may not be used with super search fields. Use EXPAND with the individual field codes instead.

Search Field Name	Search Code	Fields Searched	Search Examples	Display Codes
Application Number Group (1)	/APPS	/AP, /PRN	S 1989GB-0219641/APPS S 1989GB-0219641/APPS	ADT, AI, PRAI
Document Number Chemical Codes, all Subfields	/DN /MALL	/DNC, /DNN /M0, /M1, /M2, /M3, /M4, /M5, /M6	S C1993-056092/DN S A100/M2	DNC, DNN M2, CMC
Patent Number Group	/PATs	/PN, /FDT.PN	S GB2223255/PATs S EP-----100323/PATs S EP100323/PATs	FDT, PI
Patent Countries	/PCS	/PC, /DS	S ES/PCS S SPAIN/PCS	DS, PI, PN

- (1) Either STN or Derwent format may be used.

Additional DWPI Individual Patent Publication (often First Level Data) Search Fields

Fields that allow left truncation are indicated by an asterisk (*).

Search Field Name	Search Code	Search Examples	Display Codes
Basic Index Extended* (contains single terms from author abstracts, claims, and original titles) (2)	/BIEX	S NANOCLOUDS/BIEX	ABDE, ABEN, ABES, ABFR, ABOL, CLMDE, CLMEN, CLMES, CLMFR, CLMOL, TIDE, TIEN, TIES, TIFR, TIOL
Abstract, Original, in English* (2)	/ABEN	S ?CONDUCTIVE MATERIAL/ABEN	ABEN
Abstract, Original, in French* (2)	/ABFR	S ?MOBILIS?/ABFR	ABFR
Abstract, Original, in German* (2)	/ABDE	S ?AUTOMATISIERT?/ABDE	ABDE
Abstract, Original, in other Language* (2)	/ABOL	S CATALISADOR/ABOL	ABOL
Abstract, Original, in Spanish* (2)	/ABES	S (METODO(2A)SINTESIS)/ABES	ABES
Agent (3)	/AG	S PFIZER/AG	AG
Agent Address (3)	/AGA	S NEWCASTLE/AGA	AGA
Agent, City	/AG.CTY	S (MUNICH OR MUENCHEN)/AG.CTY	AGA
Agent, Country (code)	/AG.CNY	S NL/AG.CNY	AGA
Agent, Postal Code	/AG.ZIP	S 69134/AG.ZIP	AGA
Agent, State	/AG.ST	S NY/AG.ST	AGA
Agent, Total (3)	/AG.T	S PFIZER INC./AG.T	AG.T
Application Information, Clarivate Claims (all languages)* (2)	/APTS	S 1978US-000000357/APTS	APTS
	/CLM	S OFFICE CHAIR/CLM S BUEROSTUHL/CLM S ?CHAIR?/CLM	CLMDE, CLMEN, CLMES, CLMFR, CLMOL
Claims in English (2)	/CLMEN	S (CATALY?(2A)?REDUC?)/CLMEN	CLMEN
Claims in French (2)	/CLMFR	S (CATALYS?(2A)MICROP?)/CLMFR	CLMFR
Claims in German (2)	/CLMDE	S KATALYSATORSYSTEM?/CLMDE	CLMDE
Claims in other Languages (2)	/CLMOL	S (EMULSAO(P)OLEO)/CLMOL	CLMOL
Claims in Spanish (2)	/CLMES	S (METODO(5A)CUALQUIERA)/CLMES	CLMES
Field Availability (Individual Members)	/FA.M	S CLMEN/FA.M	FA.M
Inventor Address (3)	/INA	S HEIDELBERG/INA	INA
Inventor, City	/IN.CTY	S WIEN/IN.CTY	INA
Inventor, Country	/IN.CNY	S DE/IN.CNY	INA
Inventor, Nationality (WIPO Code)	/IN.NAT	S AT/IN.NAT	INA
Inventor, Original	/INO	S MAYER DALE J/INO	INO
Inventor, Postal Code	/IN.ZIP	S 69469/IN.ZIP	INA
Inventor, Residence (WIPO Code)	/IN.RES	S BE/IN.RES	INA
Inventor, State	/IN.ST	S OH/IN.ST	INA
Inventor, Surname	/INO.SNM	S SCHEKINEN/INO.SNM	INO
Inventor, Total (3)	/IN.T	S MAYER?/IN.T	IN.T
IPC, Initial (IICM, IICS)	/IIC	S A01B000/IIC	IIC
IPC, Initial, Additional (supplementary)	/IICA	S A01B003-36/IICA	IICA
IPC, Initial, Index (complementary)	/ICI	S B03D0103:08/ICI	ICI
IPC, Initial, Main	/IICM	S C09K007-02/IICM	IIC
IPC, Initial, Secondary	/IICS	S A01B001/IICS	IIC
Patent Assignee Address (3)	/PAA	S MUENCHEN?/PAA	PAA
Patent Assignee, City	/PA.CTY	S MUNICH/PA.CTY	PAA
Patent Assignee, Country	/PA.CNY	S BE/PA.CNY	PAA
Patent Assignee, Limitation (WIPO code)	/PA.LIM	S DE/PA.LIM	HITMEMB

Additional DWPI Individual Patent Publication (often First Level Data) Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Patent Assignee, Nationality (WIPO code)	/PA.NAT	S BE/PA.NAT	HITMEMB
Patent Assignee, Original (3)	/PAO	S 3M COMPANY/PAO	PAO
Patent Assignee, Postal Code	/PA.ZIP	S 69140/PA.ZIP	PAA
Patent Assignee, Residence (WIPO code)	/PA.RES	S DE/PA.RES	HITMEMB
Patent Assignee, State	/PA.ST	S OH/PA.ST	PAA
Patent Assignee, Total (3)	/PA.T	S BASF AG/PA.T	PA.T
Priority Application Information, Clarivate	/PRTS	S 2021WO-CA0050007/PRTS	PRTS
Priority Country, Basic (WIPO code and text)	/PRC.B	S AR/PRC.B	PRAI
Priority Date, Basic (1)	/PRD.B	S PRD.B=JUN 1998	PRAI
Priority Number, Basic	/PRN.B	S AR1968-214388/PRN.B	PRAI
Priority Year, Basic (1)	/PRY.B	S 1998/PRY.B	PRAI
Title, Original, in English* (2)	/TIEN	S PLANT PRODUCT/TIEN	TIEN
Title, Original, in French* (2)	/TIFR	S FRUIT#/TIFR	TIFR
Title, Original, in German* (2)	/TIDE	S FRUCHTFLEISCH/TIDE	TIDE
Title, Original, in other Languages * (2)	/TIOL	S METALOPORFIRINAS/TIOL	TIOL
Title, Original, in Spanish* (2)	/TIES	S FRUTOS/TIES	TIES
Update Date Agent (1)	/UPAG	S 20210101-20210601/UPAG	UPAG
Update Date Author Abstract (1)	/UPAA	S MAR 2006/UPAA	UPAA
Update Date Author Title (1)	/UPAT	S 16 APR 2005/UPAT	UPAT
Update Date Claims (1)	/UPCL	S 20050509/UPCL	UPCL
US National Patent Classification, Issued	/INCL	S 208139000/INCL	INCL
US National Patent Classification, Issued (main)	/INCLM	S 208139000/INCLM	INCL
US National Patent Classification, Issued (secondary)	/INCLS	S 624/INCLS	INCL

(1) Numeric search field that may be searched using numeric operators or ranges.

(2) The words AND, IS, OF, THE, and TO are not indexed in this field.

You may use these stop words in your search statement, however at their position a (1W)-proximity is used by the system.

(3) Search with implied (S) proximity is available in this field. Bound phrases have to be searched with quotation marks.

CITATION DATA FIELDS FROM DWPI

Citation Fields – Cited Patent

Fields that allow left truncation are indicated by an asterisk (*).

Search Field Name	Search Code	Search Examples	Display Codes
Citation Category	/CAT	S BASF/PA.D(P)(X OR I)/CAT	CDP
Citation Category, Cited	/CAT.D	S BASF/PA.D(P)(X OR I)/CAT.D	CDP
Cited Accession Number	/AN.D (or /OS.D)	S 2019-100035/AN.D	CDP
Cited Inventor	/IN.D	S BELLER M/IN.D	CDP
Cited Patent Assignee (1)	/PA.D	S HYUNDAI/PA.D	CDP
Cited Patent Assignee Code (2)	/PACO.D	S HYMR/PACO.D	CDP
Cited Patent Country	/PC.D (or /RPC)	S EP/PC.D	CDP
Cited Patent Date (3)	/PD.D (or /RPD)	S 20200102/PD.D	CDP
Cited Patent Kind Code	/PK.D (or /RPK)	S USA1/PK.D	CDP
Cited Patent Number	/PN.D (or /RPN)	S US20190062224/PN.D	CDP
Cited Patent Year (3)	/PY.D (or /RPY)	S 2019/PY.D	CDP
Origin of Citation	/ORC (or /SRT)	S OPPOSITION/ORC	CDP
Update Date, Cited (3)	/UPD	S 20211001/UPD	UPD

Citation Fields – Cited Literature

Search Field Name	Search Code	Search Examples	Display Codes
Citation Category	/CAT	S BELLER/CDL(P)(X OR I)/CAT	CDL
Citation Category, Cited	/CAT.D	S BELLER/CDL(P)(X OR I)/CAT.D	CDL
Cited Non-Patent Literature*	/CDL (or /REN)	S (TRANSDERMAL(2A)?PATCH?)/CDL	CDL
Digital Object Identifier	/DOI (or /FTDOI)	S HTTPS://DOI.ORG/10.1109/SYSCON.2015.71 16836/DOI	DOI, CDL
Origin of Citation	/ORC (or /SRT)	S ?LIPASE?/CDL(P)E/ORC	CDL
Update Date, Cited (3)	/UPD	S 20211001/UPD	UPD
XP Document Number	/XP (or /REXP)	S XP000000013/XP	XP, CDL

(1) Search with implied (S) proximity is available in this field. Bound phrases have to be searched with quotation marks.

(2) A thesaurus is available in this field.

(3) Numeric search field that may be searched using numeric operators or ranges.

Citation Fields – Citing Patents

Search Field Name	Search Code	Search Examples	Display Codes
Citation Category	/CAT	S SIEMENS/PA.G(P)X/CAT	CGP
Citation Category, Citing	/CAT.G	S SIEMENS/PA.G(P)X/CAT.G	CGP
Citing Accession Number	/AN.G (or /OS.G)	S 2019-000006/AN.G	CGP
Citing Inventor	/IN.G	S SMITH A/IN.G	CGP
Citing Patent Assignee (1)	/PA.G	S ROHM HAAS/PA.G	CGP
Citing Patent Assignee Code (2)	/PACO.G	S MICT-C/PACO.G	CGP
Citing Patent Country	/PC.G	S AU/PC.G	CGP
Citing Patent Date (3)	/PD.G	S 20210105/PD.G	CGP
Citing Patent Kind Code	/PK.G	S CNA/PK.G	CGP
Citing Patent Number	/PN.G	S JP06000043B/PN.G	CGP
Citing Patent Year (3)	/PY.G	S 2017-2019/PY.G	CGP
Origin of Citation	/ORC (or /SRT)	S EP/PC.G(P)THIRDPARTY/ORC	CGP
Update Date, Citing (3)	/UPG	S 20211001/UPG	UPG

Citation Count Fields

Search Code	Definition	Search Examples	Display Codes
/ANC.D (3)	Cited DWPI Accession Number Count	S ANC.D>20	CITC
/ANC.G (3)	Citing DWPI Accession Number Count	S 10-20/ANC.G	CITC
/CRC (3)	Cited Literature Reference Count	S CRC<10	CITC
/PCC.D (3)	Cited Patents Country Count	S 3-5/PCC.D	CITC
/PCC.G (3)	Citing Patents Country Count	S 10/PCC.G	CITC
/PNC.D (3)	Cited Patents Count	S PNC.D>30	CITC
/PNC.G (3)	Citing Patents Count	S 20-30/PNC.G	CITC
/REC (3)	Cited Reference Count (total)	S REC>100	CITC

Citation Fields – Derwent Family Members with Citations

Search Code	Definition	Search Examples	Display Codes
/PC.F	Patent Country of Family Member (cited, citing)	S CN/PC.F(P)JP/PC.D	CDP,CGP,CDL
/PK.F	Patent Kind Code of Family Member (cited, citing)	S EPB#/PK.F(P)O/ORC	CDP,CGP,CDL
/PN.F	Patent Number of Family Member (cited, citing)	S EP1003890/PN.F	CDP,CGP,CDL

Examiner Fields of Search

Search Code	Definition	Search Examples	Display Codes
/EXF.CPC	Examiner's Field of Search, CPC	S A61K/EXF.CPC	EXF, EXFA
/EXF.IPC	Examiner's Field of Search, IPC	S C12N0005/EXF.IPC	EXF, EXFA
/EXF.JPC	Examiner's Field of Search, JPC	S C07D0239-00/EXF.JPC	EXF, EXFA
/EXF.USPC	Examiner's Field of Search, USPC	S 101221000/EXF.USPC	EXF, EXFA

(1) Search with implied (S) proximity is available in this field. Bound phrases have to be searched with quotation marks.

(2) A thesaurus is available in this field.

(3) Numeric search field that may be searched using numeric operators or ranges.

Property Fields⁽¹⁾

In DWPI a numeric search for a specific set of physical properties (/PHP) is available within the English text fields (titles, abstracts, claims). The numeric values are not displayed as single fields, but highlighted within the hit displays.

Use EXPAND/PHP to search for all available physical properties. A search with the respective field codes will be carried out in all database fields with English text. The /PHP index contains a complete list of codes and related text for all physical properties available for numeric search.

Field Code	Property	Unit	Symbol	Search Examples
/AOS	Amount of Substance	Mol	mol	S 10 /AOS
/BIR	Bit Rate	Bit/Second	bit/s	S 8000-10000/BIR
/BIT	Stored Information	Bit	Bit	S BIT > 3 MEGABIT
/CAP	Capacitance	Farad	F	S 1-10 MF/CAP
/CATA	Catalytic Activity	Katal	kat	S 1-10/KATA
/CDN	Current Density	Ampere/Square Meter	A/m ²	S CDN>10 A/M**2
/CMOL	Molarity, Molar Concentration	Mol/Liter	mol/L	S UREA/BI (S) 8/CMOL
/CON	Conductance	Siemens	S	S 1S-3/CON
/DB	Decibel	Decibel	dB	S DB>50
/DEG	Degree	Degree	°	S CYLINDER/BI (S) 45/DEG
/DEN (/C)	Density (Mass Concentration)	Kilogram/Cubic Meter	kg/m ³	S 5E-3-10E-3/DEN
/DEQ	Dose Equivalent	Sievert	Sv	S 100/DEQ
/DOA	Dosage	Milligram/Kilogram/Day	mg/kg/day	S 300/DOA
/DOS (/LD50)	Dosage	Milligram/Kilogram	mg/kg	S DOS>0.8
/DV	Viscosity, dynamic	Pascal * Second	Pa * s	S DV>5000
/ECH (/CHA)	Electric Charge	Coulomb	C	S 0.0001-0.001/ECH
/ECO (/ECND)	Electrical Conductivity	Siemens/Meter	S/m	S ECO>800 S/M (15A) AQUEOUS
/ELC (/ECC)	Electric Current	Ampere	A	S 1-10/ELC
/ELF (/ECF)	Electric Field	Volt/Meter	V/m	S 200/ELF
/ENE	Energy	Joule	J	S DROPLETS (10A) 40 JOULE - 70 JOULE /ENE
/ERE (/ERES)	Electrical Resistivity	Ohm * Meter	Ohm * m	S ERE>0.1
/FOR	Force	Newton	N	S 50 N /FOR
/FRE (/F)	Frequency	Hertz	Hz	S OSCILLAT?/BI (S) 1- 3/FRE
/IU	International Unit	none	IU	S IU>1000 (P) VITAMIN A
/KV	Viscosity, kinematic	Square Meter/Second	m ² /s	S METHYLPOLYSILOXANES/BI (10A) 200-300 CST/KV
/LEN (/SIZ)	Length, Size	Meter	m	S 1-4/LEN
/LUME	Luminous Emissance, Illuminance	Lux	lx	S 10-50/LUME
/LUMF	Luminous Flux	Lumen	Lm	S LUMF>1000
/LUMI	Luminous Intensity	Candela	cd	S LUMI<4
/M	Mass	Kilogram	kg	S ALLOY/BI (30A) 1E-10-1E-5/M
/MCH	Mass to Charge Ratio	none	m/z	S MCH=1

Property Fields⁽¹⁾ (cont'd)

Field Code	Property	Unit	Symbol	Search Examples
/MFD (/MFS)	Magnetic Flux Density	Tesla	T	S MFD>102
/MFR (/MFL)	Mass Flow Rate	Kilogram/Second	kg/s	S MFR<0.1
/MFST	Magnetic Field Strength	Ampere/Meter	A/m	S 40-50/MFST
/MM (/MW, /MOM)	Molar Mass	Gram/Mol	g/mol	S 2000-3000 G/MOL/MM
/MOLS	Molality of Substance	Mol/Kilogram	mol/kg	S 01.-10 MOL/KG/MOLS
/MVR	Melt Volume Rate, Melt Flow Rate	none	g/10 min	S 3/MVR
/PER	Percent (Proportionality)	none	%	S POLYMER?/AB (5A) 4/PER
/PHV (/PH)	pH Value	pH	pH	S 7.4-7.6/PHV
/POW (/PW)	Power	Watt	W	S "HG-XE-?" /BI (S) 100-200 WATT/POW
/PPM	Parts per million	PPM	ppm	S 100 PPM /PPM (10A) ADDITIVE/BI
/PRES (/P)	Pressure	Pascal	Pa	S (VACUUM (5A) DISTILL?) /BI (S) 1000-1100/PRES
/RAD	Radioactivity	Becquerel	Bq	S 1-10/RAD
/RES	Electrical Resistance	Ohm	Ohm	S SENSOR /BI (S) 10- 100/RES
/RI	Refractive Index	none		S 3-4/RI
/RSP	Rotational Speed	Revolution/Minute	rpm	S 2 RPM - 100 RPM /RSP (S) ENGINE/BI
/SAR	Area /Surface Area	Square Meter	m ²	S PLATE/BI (S) 10 M**2 - 100 M**2 /SAR
/SOL (/SLB)	Solubility	Gram/100 gram	g/100 g	S SOL>20 G/100G (5A) WATER
/SSAM	Specific Surface Area, Mass	Square Meter/ Kilogram	m ² /kg	S 9/SSAM
/STSC	Surface Tension, Spring Constant	Joule /Square Meter	J/m ²	S 60 J/M**2/STSC
/TCO (/TCND)	Thermal Conductivity	Watt/Meter * Kelvin	W/m * K	S 1/TCO (S) HEAT?
/TEMP (/T)	Temperature	Kelvin	K	S 20-25/TEMP
/TEX	Tex	Gram/Kilometer	g/km	S 1-5/TEX
/TIM	Time	Second	s	S ?INCUB?/BI (10A) 50 S - 150 S /TIM
/VEL (/V)	Velocity	Meter per Second	m/s	S REDUC?/BI (S) 1E-3-5E-3/VEL
/VELA	Velocity, Angular	Radian/Second	rad/s	S VELA>10
/VLR	Volumetric Flow Rate	Cubic Meter/Second	m ³ /s	S 1 M**3/S - 2 M**3/S /VLR (S) ABRASIVE
/VOL	Volume	Cubic Meter	m ³	S 1E-8-2E-8/VOLEX
/VOLT	Voltage	Volt	V	S TENSION/BI (10A) 5E-3 V <VOLT<7E-3 V

(1) Exponential format is recommended for the search of particularly high or low values, e.g. 1.8E+7 or 1.8E7 (for 18000000) or 9.2E-8 (for 0.000000092).

IPC Thesaurus

The classifications and catchwords for the main headings and subheadings from the current (8th) edition of the WIPO International Patent Classification (IPC) manual are available. The classifications from the previous editions (1-7) are also available as separate thesauri. To EXPAND and SEARCH in the thesauri for editions 1-7, use the field code followed by the edition number, e.g., /IPC2, for the 2nd edition. Catchwords are included only in the thesauri for the 8th, 7th, 6th, and 5th editions.

Relationship Code	Content	Search Examples
ADVANCED (ADV) ALL BRO (MAN) BT CORE (COR) ED	Advanced Codes for the Core Level IPC code All Associated Terms (BT, SELF, NT, RT) Complete Class Broader Term (SELF, BT) Core Codes for the Advanced Level IPC code Complete title of the SELF term and IPC manual edition	E A61K006-02+ADV/IPC E C01C003-00+ALL/IPC E C01C+BRO/IPC E C01F001-00+BT/IPC E C03B0001-02+COR/IPC E C01F001-00+ED/IPC
HIE	Hierarchy Term (Broader and Narrower Term) (BT, SELF, NT)	E C011003-00+HIE/IPC
INDEX KT	Complete title of the SELF term Keyword Term (catchwords) (SELF, KT)	E C01F001-00+INDEX/IPC E CYANOGEN+KT/IPC
NEXT NT PREV RT (SIB) TI	Next Classification Narrower Terms (SELF, NT) Previous Classification Related Terms (SELF, RT) Complete Title of the SELF Term and Broader Terms (BT, SELF)	E C01C001-00+NEXT5/IPC E C01C+NT/IPC E C01C001-12+PREV10/IPC E C01C003-20+RT/IPC E C01F001-00+TI/IPC

CPC, ECLA (/EPC) and ICO Thesauri

These thesauri are available in the /CPC search field, /EPC search field (for ECLA codes) and /ICO search field ('in-computer-only') Classification. All relationship codes can be used with both the EXPAND and SEARCH commands.

Relationship Code	Content	Search Examples
ALL AUTO (1) BT CODE	All usually required terms (BT, SELF, CODE, DEF) Automatic relationship (BT, SELF, CODE, DEF) Broader terms (BT, SELF) Classification Code (SELF, CODE)	E C12M0001-34H2+ALL/EPC E G01J003-443+AUTO/EPC E G01J0003-443+BT/EPC E SCRAPER BIASING MEANS+CODE/EPC
DEF HIE	Definition (SELF, DEF) Hierarchy terms (all broader and narrower terms) (BT, SELF, DEF, NT)	E B65G0045-16+DEF/EPC E A01B0001+HIE/EPC
KT MAX NEXT NEXT(n) NT PREV PREV(n) TI	Keyword terms (SELF, KT) All associated terms Next classification within the same class (SELF, NEXT) Next n classification within the same class Narrower term Previous Code within the same class (SELF, PREV) Previous n classifications within the same class Complete Title of the SELF Term and Broader Terms (BT, SELF)	E LASER+KT/EPC E G01J0003-44B+MAX/EPC E A01B0001-24+NEXT/EPC E A01B0001-24+NEXT3/EPC S G05B0001-03+NT/EPC E L60H0001:00A+PREV/ICO E L60H0001:00A+PREV1/ICO E G05B0001-03+TI/EPC

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

F-Term (/FTERM) Thesaurus

This thesaurus is available in the F-Term (/FTERM) field that contains patent classification from the Japanese Patent Office from February 2009 to the present.

Relationship Code	Content	Search Examples
ALL BT CODE DEF HIE KT NT RFI TI	All associated terms (BT, SELF, NT, RT) Broader Term (SELF, BT) Code for the thesaurus text term Definition Hierarchy Terms (all broader and narrower terms) Keyword Term Narrower Term Related FI (File Indexing) classification Term Complete Title of the SELF Term and Broader Terms (BT, SELF)	E 2B002/AA05+ALL/FTERM E 2B002/AA05+BT/FTERM E 2B002/BA13+CODE/FTERM E 2B002/BA13+DEF/FTERM E 2B002/AA05+HIE/FTERM E 2B002/AA05+KT/FTERM E 2B002/AA09+NT/FTERM E 2B002/AA09+RFI/FTERM E 2B002/AA09+TI/FTERM

FI-Term (/FCL) Thesaurus

This thesaurus is available in the FI-Term (/FCL) field that contains patent classification from the Japanese Patent Office.

Relationship Code	Content	Search Examples
ALL BT DEF HIE INDX MAX NOTE NT RT TI	All usually required associated terms Broader Term (SELF, BT) Definition Hierarchy Terms (all broader and narrower terms) Index Note All associated Terms Scope Notes Narrower Term Related Term Complete Title of the SELF Term and Broader Terms (BT, SELF)	E A01B0003-00+ALL/FCL E H02B0001-02+BT/FCL E H05B0041-392+DEF/FCL S H02B0001-02C+HIE/FCL E C07C CSP+INDX/FCL E B01B0001-08+MAX/FCL E B23D+NOTE/FCL E H05B0041-392+NT/FCL E H05B+RT/FCL E A01B0001-12+TI/FCL

US National Patent Classification (/NCL) Thesaurus

The US National Patent Classification thesaurus is available online in field /NCL. All relationship codes can be used with both the EXPAND and SEARCH commands.

Relationship Code	Content	Search Examples
ALL AUTO (1) BT CODE DEF HIE KT MAX NEXT NEXT(n) NT PREV PREV(n) TI	All usually required terms (BT, SELF, DEF, NT) Automatic relationship (BT, SELF, DEF, NT) Broader Terms (BT, SELF) Classification Code (SELF, CODE) Definition (SELF, DEF, DEF2, DEF3, DEF4) Hierarchy Terms (BT, SELF, DEF, NT) Keyword Terms (SELF, KT) All associated Terms (BT, SELF, DEF, DEF2, DEF3, DEF4, NT, KT) Next classification within the same class Next n classifications within the same class Narrower Terms (SELF, NT) Previous Code within the same class Previous n classifications within the same class Complete title of the SELF and the Broader Terms including their definitions (BT (DEF), SELF, DEF)	E 257E21685+ALL/NCL E 02416300R+AUTO/NCL E 02416300R+BT/NCL E APPAREL+CODE/NCL E G9B031001+DEF/NCL E 23548700+HIE/NCL E APPAREL+KT/NCL E G9B031000+MAX/NCL E G9B033035+NEXT/NCL E G9B033035+NEXT2/NCL S 257E21685+NT/NCL E 235462260+PREV/NCL E 235462260+PREV3/NCL E 052002110+TI/NCL

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

Manual Codes Thesauri (CPI AND EPI)

Field	Relationship Code	Content	Search Examples
/MC	ALL AUTO (1) BT NT	All Associated Terms (BT, SELF, HNTE, DEF, NT) Automatic Relationship (SELF, HNTE, DEF) Broader Terms (BT, SELF) Narrower Terms (NT, SELF)	E A03-A04A1+ALL/MC E S01-B05+AUTO/MC E S06-B02A+BT/MC S S06-B02+NT/MC

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

DWPI Title Terms

The automatic relationship is SET ON by default, so that forbidden terms will cause automatic retrieval of the preferred terms in a SEARCH.

Field	Relationship Code	Content	Search Examples
/TT	ALL AUTO (1) UF USE	All Associated Terms (SELF, USE, UF) Automatic Relationship (SELF, USE) Used for (Preferred and Forbidden Terms - SELF, UF) Use (Forbidden and Preferred Terms – SELF, USE)	E ABLATION+ALL/TT S ABLATE+AUTO/TT E FABRICATE+UF/TT S FABRICATED+USE/TT

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

Patent Assignee Code Dictionary

The list of Clarivate (UK) Limited-assigned company codes for patent assignees matched with company names is available in field /PACO. This feature allows you to easily and comprehensively identify the company names associated with a code, or to identify the code(s) used for a company name. Expanding in field /PACO (Patent Assignee Code) provides the alphabetical list of codes, single words and the full name from the company field (/PA). Each code is listed with its frequency in field /PACO and with the number of associated terms (AT) in the dictionary.

Field	Relationship Code	Content	Search Examples
/PACO	ALL DEF	All patent assignee code(s) defined for the name All name definitions for the given code	E BAYER+ALL/PACO E FARB+DEF/PACO

Polymer Indexing Thesaurus

DWPI Polymer Indexing Thesaurus is available online in field /PLE. All relationship codes can be used with both the EXPAND and SEARCH commands.

Field	Relationship Code	Content	Search Examples
/PLE	ALL	All Associated Terms (BT, SELF, NOTE, USE, SEE, UF, NT, RT)	E Q8457+ALL/PLE
	AUTO (1)	Automatic Relationship (SELF, USE, UF)	E CANS<APPLICATIONS>+ALL/PLE
	BT	Broader Terms (also BT1=1 st Level, BT2=2 nd Level, etc.)	E BY-PRODUCTS/PLE
	HIE	Hierarchy Terms (BT, SELF, NT)	S E4+AUTO
	KT	Keyword Terms (Multi-word Phrases containing the specified Keyword Term)	E Q8457+BT/PLE
	NT	Narrower Terms (also NT1=1 st Level, NT2=2 nd Level, etc.)	E Q8399+HIE/PLE
	RT	Related Terms (see also)	E Q8399+KT/PLE
	UF	Used for (Preferred and Forbidden Terms)	E Q7034+NT/PLE
	USE	Use (Forbidden and Preferred Terms)	E DIELECTRIC CONSTANT <PROPERTIES>+UF/PLE
			E POWER FACTOR/PLE

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

Plasdoc Key Serials Dictionary

The Plasdoc Key Serials codes in field /KS can be looked up in an online dictionary. You may expand on the definitions for the codes in field /KS, e.g., => E GASEOUS/KS will provide an alphabetical list around the term gaseous. The list also shows the number of codes associated with the term (AT column).

Field	Relationship Code	Content	Search Examples
/KS	ALL	All Associated Terms (CODE, DEF)	E GASEOUS+ALL/KS

DWPI Compound Numbers (/DCN) Thesaurus

For DWPI Compound Numbers (/DCN), the USE/UF relationships are available to see the definitions. All relationship codes can be used with both the EXPAND and SEARCH commands.

Field	Relationship Code	Content	Search Examples
/DCN	ALL UF USE	All associated terms (SELF, USE, UF) Used for terms (SELF, UF) Use terms (SELF, USE)	E R09609+ALL/DCN E R22401+UF/DCN E ACETIC ACID+USE/DCN

DWPI Registry Numbers (/DRN) Thesaurus

For DWPI Registry Numbers (/DRN), the USE/UF relationships are available to see the definitions. All relationship codes can be used with both the EXPAND and SEARCH commands.

Field	Relationship Code	Content	Search Examples
/DRN	ALL UF USE	All associated terms (SELF, USE, UF) Used for terms (SELF, UF) Use terms (SELF, USE)	E 0495+ALL/DRN E 1314+UF/DRN E ACETIC ACID+USE/DRN

DWPI Invention Level

DISPLAY and PRINT Formats

Any combination of formats may be used to display or print answers. Multiple codes must be separated by spaces or commas, e.g., D L1 1-5 TI AU. The fields are displayed or printed in the order requested.

Hit-term highlighting is available for all fields. Highlighting must be ON during SEARCH to use the HIT, KWIC, and OCC formats.

Format	Content	Examples
AB	Abstract (contains value-added data)	D AB
ABDT (1)	Abstract, Documentation	D ABDT
ABEQ	Abstract, Equivalent	D ABEQ
ABEX (1)	Abstract, Extension	D ABEX
ACTN	Mechanism of Action	D ACTN
ACTV	Activity	D ACTV
ADT (2)	Application Details	D ADT
ADT.B (2)	Application Details, Basic	D ADT.B
ADV	Advantage	D ADV
AI (AP) (2)	Application Information	D AI
AI.B	Application Information, Basic	D AI.B
ALE	Alerting Abstract, First Section	D ALE
AN	Accession Number	D AN
ANX	Crossover Accession Number	D ANX
AW	Additional Words	D AW
CMC	Chemical Code	D CMC
CPC	Cooperative Patent Classification	D CPC
CPC.TAB	CPC, Tabular Display of CPC, CPC.KW, CPC.ACD, CPC.VER	D CPC.TAB
CR (XR)	Cross Reference	D CR
CYC	Country Count	D CYC
DC	DWPI Class	D DC
DCN	DWPI Compound Number	D DCN
DCR	Chemical Resource Number	D DCR
DCRU	Chemical Resource Number, Unlinked	D DCRU
DETD	Detailed Description	D DETD
DN	Document Number (DNC and DNN)	D DN
DNC	Document Number CPI	D DNC
DNN	Document Number Non-CPI	D DNN
DRN	DWPI Registry Number	D DRN
DRWD	Description of Drawings	D DRWD
DRWN	Number of Drawings	D DRWN
DS	Designated State	D DS
DUPD	DWPI Update (formerly Derwent Week), first and latest	D DUPD
ED	Entry Date	D ED
EPC (ECLA, EPCLA)	European Patent Classification	D EPC
FA	Field Availability	D FA
FCL (JPC)	Japanese Patent Office Classification (FI-Terms)	D FCL
FDT	Filing Details	D FDT
FG (AM)	Fragmentation Code (PLASDOC)	D FG
FS	File Segment	D FS
FTRM (FTERM, FTCLA, JPCLA)	Japanese Patent Office Classification (F-Terms)	D FTRM
GI	Graphic Information	D GI
GINF (GIS)	Graphic Image(s) Information	D GINF
IC	IPC, Main and Secondary (IPC 1-7)	D IC
ICA	IPC, Additional (supplementary, IPC 1-7)	D ICA
ICI	IPC, Index (complementary, IPC 1-7)	D ICI
ICM	IPC, Main (IPC 1-7)	D ICM
ICO	ICO (in-computer-only) Classification	D ICO

DWPI Invention Level

DISPLAY and PRINT Formats (cont'd)

Format	Content	Examples
ICS	IPC, Secondary (IPC 1-7)	D ICS
IN (AU)	Inventor	D IN
IPC	International Patent Classification (ICM, ICS, ICA, ICI, IPCI, IPCR)	D IPC
IPC.TAB	IPC, Tabular Display of IPC, IPC.KW, IPC.ACD, IPC.VER	D IPC.TAB
IPCI	IPC, Initial	D IPCI
IPCR	IPC, Reclassified	D IPCR
IT (KW)	Index Term	D IT
KS	Plasdoc Key Serials	D KS
M0-M6	Chemical Codes	D M0
MC	Manual Code	D MC
NCL	US National Patent Classification, Current	D NCL
NOV	Novelty	D NOV
PA (CS)	Patent Assignee	D PA
PATS	Patent Number Group	D PATS
PI (2,3)	Patent Information (including designated states)	D PI
PI.B (2,3)	Patent Information, Basic	D PI.B
PLC	Polymer Coding Plasdoc	D PLC
PLE	Polymer Indexing Enhanced	D PLE
PN (2,3)	Patent Information (without designated states)	D PN
PN.B	Patent Information, Basic (without designated states)	D PN.B
PNK	Patent Number/Kind Code	D PNK
PNK.B	Patent Number/Kind Code, Basic	D PNK.B
PNC	Patent Number Count	D PNC
PRAI (PRN) (2)	Priority Information	D PRAI
RIN	Ring Index Number	D RIN
RINU	Ring Index Number, unlinked	D RINU
TECH	Technology Focus	D TECH
TI	Title	D TI
TT	Title Terms	D TT
UADV	Use/Advantage Section	D UADV
UP	Update Date	D UP
UPA	Update Date Polymer Indexing	D UPA
UPAB	Update Date Abstract	D UPAB
UPB	Update Date Chemical Code	D UPB
UPCP	Update Date Cooperative Patent Classification	D UPCP
UPFT	Update Date Japanese Patent Classification	D UPFT
UPIC	Update Date International Patent Classification	D UPIC
UPIN	Update Date Inventor	D UPIN
UPIT (UPKW)	Update Date Index Term	D UPIT
UPPA	Update Date Patent Assignee	D UPPA
UPMC	Update Date Manual Code	D UPMC
UPP	Update Date Patent Family	D UPP
UPS	Update Date SDI	D UPS
UPTI	Update Date Enhanced Title	D UPTI
USE	Use	D USE

(1) This field is available in WPIX only.

(2) Application, priority and patent numbers are available in Derwent and STN format. The format for DISPLAY, PRINT, SELECT and SORT is controlled by the Messenger SET PATENT command. The STN format is default. 'SET PAT DERWENT' changes (permanently) to the Derwent format. To change to the STN format again, enter 'SET PAT STN'.

(3) Basic patents are identified with an asterisk (*), Equivalent-Treated-as-Basic are identified with a capital letter B, and Non-Conventional Equivalents are identified with a hash mark (#).

DWPI Invention Level

Predefined Formats

Format	Content	Examples
ABS	AN, CR, AB, UPAB, ABEQ	D TI PA ABS
ALL (1)	All invention level data available for a given record, excluding the Equivalent (ABEQ), Documentation (ABDT), and Extension (ABEX) abstracts and the chemical coding and polymer indexing: AN, CR, ANX, DNC, DNN, TI, DC, IN, PA, CYC, PN, ADT, FDT, PRAI, IPC, CPC, EPC, ICO, NCL, FCL, FTRM, AB, UPAB, FS, MC. Short compressed version.	D ALL
ALLG (1)	ALL, plus graphic image	D ALLG
DALL (1)	ALL, delimited for post processing	D DALL
IALL (1)	ALL, indented with text labels	D IALL
IALL.G (1)	ALLG, indented with text labels	D IALL.G
ANL	Accession Number List only	D ANL
APPS (1)	ADT, PRAI	D APPS
BASIC (1)	AN, CR, ANX, DNC, DNN, TI, DC, IN, PA, PNC, CYC, PN.B, ADT.B, PRAI, AB, UPAB, FS	D BASIC
BIB (1)	AN, CR, DNC, DNN, TI, DC, IN, PA, CYC, PI, ADT, FDT, PRAI	D BIB
IBIB (1)	BIB, indented with text labels	D IBIB
BRIEF	AN, CR, ANX, DNC, DNN, TI, DC, PA, AB, UPAB	D BRIEF
BRIEFG	BRIEF, plus graphic image	D BRIEFG
IBRIEF	BRIEF, indented with text labels	D IBRIEF
IBRIEFG	BRIEFG, indented with text labels	D IBRIEFG
CODE (IND)	AN, DC, IPC, CPC, EPC, ICO, NCL, FCL, FTRM, MC, IT, DRN, PLC, PLE, CMC	D CODE
CPC.TAB	Cooperative Patent Classification, Tabular Display	D CPC.TAB
FAM (1)	PI, ADT, FDT, PRAI	D FAM
FULL (1,2)	All invention level data available for a given record plus Technology Focus (TECH) and Documentation (ABDT) or Extension abstracts (ABEX), excluding the Equivalent abstracts (ABEQ) and the chemical coding and polymer indexing: AN, CR, ANX, DNC, DNN, TI, DC, IN, PA, CYC, PN, ADT, FDT, PRAI, IPC, CPC, EPC, ICO, NCL, FCL, FTRM, AB, UPAB, TECH, ABEX, ABDT, FS, MC. Short compressed version.	D FULL
FULLG (1,2)	FULL, plus graphic image	D FULLG
IFULL (1,2)	FULL, indented with text labels	D IFULL
IFULLLG (1,2)	FULLLG, indented with text labels	D IFULLLG
IPC	IC (ICM, ICS), ICA, ICI, IPCI, IPCR	D IPC
IPC.TAB	International Patent Classification, Tabular Display	D IPC.TAB
MAX (1,2)	All invention level data available for a given record, including the chemical coding, and polymer indexing as well as Equivalent (ABEQ), Documentation (ABDT) and Extension (ABEX) abstracts: AN, ED, CR, ANX, DNC, DNN, TI, AW, DC, IN, PA, CYC, PN, ADT, FDT, PRAI, IPC, CPC, EPC, ICO, NCL, FCL, FTRM, AB, UPAB, SL, ABEQ, TECH, ABEX, ABDT, IT, FS, MC, PLC, PLE, CMC	D MAX
MAXG (1,2)	MAX, plus GI, GINF	D MAXG
IMAX (1,2)	MAX, indented with text labels	D IMAX
IMAXG (1,2)	MAXG, indented with text labels	D IMAXG
PATS (1)	PI, FDT	D PATS
SCAN (3)	AN, TI (random display, no answer numbers)	D SCAN
STD (1)	AN, CR, DNC, DNN, TI, DC, IN, PA, CYC, PN, ADT, FDT, PRAI, IPC (STD is the default)	D STD
ISTD (1)	STD, indented with text labels	D ISTD
SUM	AN, TI, NOV	D SUM
TRIAL (TRI, SAMPLE, SAM)	AN, CR, ANX, DNC, DNN, TI, DC, IPC, CPC, EPC, ICO, MC	D TRIAL
UPP	Update Patent Family (patent family information plus update dates)	D UPP

(1) Application, priority and patent numbers are available in Derwent and STN format. The format for DISPLAY, PRINT, SELECT and SORT is controlled by the Messenger SET PATENT command. The STN format is default. 'SET PAT DERWENT' changes (permanently) to the Derwent format. To change to the STN format again, enter 'SET PAT STN'.

(2) ABDT and ABEX are available in WPIX only.

(3) SCAN must be specified on the command line, i.e., D SCAN or DISPLAY SCAN.

Additional DWPI Individual Patent Publication (often First Level Data) Display and Print Formats

Format	Content	Examples
ABDE	Abstract, Original, in German	D ABDE
ABEN	Abstract, Original, in English	D ABEN
ABES	Abstract, Original, in Spanish	D ABES
ABFR	Abstract, Original, in French	D ABFR
ABOL	Abstract, Original, in other languages	D ABOL
AG	Agent	D AG
AG.T	Agent, Total	D AG.T
AGA	Agent Address	D AGA
APTS	Application Information, Clarivate	D APTS
CLM	Claims (all languages)	D CLM
CLMDE (1)	Claims in German	D CLMDE
CLMEN (1)	Claims in English	D CLMEN
CLMES (1)	Claims in Spanish	D CLMES
CLMFR (1)	Claims in French	D CLMFR
CLMOL (1)	Claims in other languages	D CLMOL
GI.M	Graphic Information, Member Patent	D GI.M
IIC	IPC, Initial (IICM, IICS)	D IIC
IICA	IPC, Initial, Additional (supplementary)	D IICA
IICI	IPC, Initial, Index (complementary)	D IICI
IICM	IPC, Initial, Main	D IICM
IICS	IPC, Initial, Secondary	D IICS
IN.T	Inventor, Total	D IN.T
INA	Inventor Address	D INA
INCL	National Classification, Issued	D INCL
INO	Inventor, Original	D INO
IPC.TAB.M	International Patent Classification, Tabular Display	D IPC.TAB.M
PA.T	Patent Assignee, Total	D PA.T
PAA	Patent Assignee Address	D PAA
PAO	Patent Assignee, Original	D PAO
PRTS	Priority Application Information, Clarivate	D PRTS
TIDE	Title, Original, in German	D TIDE
TIEN	Title, Original, in English	D TIEN
TIES	Title, Original, in Spanish	D TIES
TIFR	Title, Original, in French	D TIFR
TIOL	Title, Original, in other languages	D TIOL
UPAA (1)	Update Date Author Abstract	D UPAA
UPAG (1)	Update Date Agent	D UPAG
UPAT (1)	Update Date Author Title	D UPAT
UPCL	Update Date Claim	D UPCL

(1) Custom display only.

Additional DWPI Individual Patent Publication (often First Level Data) Predefined Formats

Format	Content	Examples
CPC.TAB.M IPC.TAB.M MEMB (1)	Cooperative Patent Classification, tabular display, individual members International Patent Classification, tabular display, individual members All additional publication level data available for a given record including original abstracts and claims, as well as fields showing publication level composition: PN, TIEN, TIDE, TIFR, TIES, TIOL, AG, IN, INO, INA, PA, PAO, PAA, ADT, APTS, FDT, PRAI, PRTS, IPC, IIC, IICI, IICA, CPC, EPC, ICO, NCL, INCL, FCL, FTRM, ABEQ, ABEN, ABDE, ABFR, ABES, ABOL, CLM, UPCL	D CPC.TAB.M D IPC.TAB.M D MEMB
MEMBG (1) MEMBB (1)	MEMB, short compressed version, plus graphic image All additional publication level data available for a given record including original abstracts and claims, as well as fields showing publication level composition: PN, TI, TIEN, TIDE, TIFR, TIES, TIOL, AG.T, IN.T, PA.T, ABEN, ABDE, ABFR, ABES, ABOL, CLM	D MEMBG D MEMBB
MEMBF (1,2)	All publication level data available for a given record AN, ED, CR, ANX, DNC, DNN, TI, TIEN, TIDE, TIFR, TIES, TIOL, AW, DC, AG, IN, INO, INA, PA, PAO, PAA, CYC, PN, ADT, APTS, FDT, PRAI, PRTS, IPC, IIC, IICI, IICA, CPC, EPC, ICO, NCL, INCL, FCL, FTRM, AB, ABEQ, TECH, ABEX, ABDT, ABDE, ABEN, ABFR, ABES, ABOL, CLM, UPCL, IT, FS, MC, FA	D MEMBF
MEMBFG (1,2)	MEMBF, plus graphic image	D MEMBFG

(1) Application , priority and patent numbers are available in DERWENT and STN format. The format for DISPLAY, PRINT, SELECT and SORT is controlled by the Messenger SET PATENT command. The STN format is default. 'SET PAT DERWENT' changes (permanently) to the DERWENT format. To change to the STN format again, enter 'SET PAT STN'.

(2) ABDT and ABEX are available in WPIX only.

DWPI Citation Data Predefined Display Formats

Format	Content	Examples
CITD (RE) CITDA CITN CITNA	EXF, CDP, CDL EXFA, CDPA, CDLA CITC, EXF, CDP, CDL, CGP CITC, EXFA, CDPA, CDLA, CGPA	D CITD D CITDA D CITN D CITNA

Special Formats with Hit Term Highlighting

Format	Content	Examples
HIT HITCMC HITCODE	All fields containing hit terms Hit chemical coding DC, IPC, CPC, EPC, NCL, FCL, FTRM, IT, DRN, MC, PLC, PLE, CMC; containg hit terms	D HIT D HITCMC D HITCODE
HITMEMB HITPLC HITPLE	All individual publications containing hit terms Hit polymer coding Hit polymer indexing	D HITMEMB D HITPLC D HITPLE
KWIC OCC	All hit terms plus a maximum of 50 words on either side List of display fields containing hit terms	D KWIC D OCC

HIT Structure Formats for DCR and DWPIM HIT Structures

Format	Content	Examples
ALLSTR	All DCR structures pertaining to the DWPI record including AN.S, CN.P, CN.S, MF	D ALLSTR
HITSTR	DCR hit structure(s) including AN.S, CN.P, CN.S, MF	D HITSTR
FRAGHITSTR	DCR structure for a fragmentation code hit paragraph	D FRAGHITSTR
AHITSTR	Assembled DWPIM HITSTR including parts of the Markush structure	D AHITSTR
BHITSTR	Assembled DWPIM HITSTR plus definitions for unmatched G-groups that are visible in the assembled display	D BHITSTR
FHITSTR	Complete DWPIM HIT Markush structure(s)	D FHITSTR

DWPI Invention Level

SELECT, ANALYZE, and SORT Fields

The SELECT command is used to create E-numbers containing terms taken from the specified field in an answer set.

The ANALYZE command is used to create an L-number containing terms taken from the specified field in an answer set.

The SORT command is used to rearrange the search results in either alphabetic or numeric order of the specified field(s).

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Accession Number	AN	Y	Y
Activity	ACTV	Y	N
Application Country	AC	Y	N
Application Country, Basic	AC.B	Y (5)	N
Application Date	AD	Y (5)	N
Application Date, Basic	AD.B	Y (5)	N
Application Number	AP (AI, ADT)	Y (2,5)	Y
Application Number Group	APPS	Y (2,3)	N
Application Number, Basic	AP.B (AI.B)	Y (2,5)	N
Application Number, Year	AP.YR	Y	N
Application Year	AY	Y (5)	N
Application Year, Basic	AY.B	Y (5)	N
Chemical Resource Number	DCR	Y (5)	N
Chemical Resource Number, unlinked	DCRU	Y (5)	N
Chemical Resource Number, with role	DCR.WR	Y (5)	N
Cooperative Patent Classification	CPC	Y	N
Country Count	CYC	Y	Y
Cross Reference	CR (XR)	Y	N
Crossover Accession Number	ANX	Y	N
Designated State	DS	Y (5)	N
Document Number (DNC and DNN)	DN	Y (4)	N
Document Number CPI	DNC	Y	Y
Document Number Non CPI	DNN	Y	Y
DWPI Class	DC	Y	Y
DWPI Compound Number	DCN	Y (5)	N
DWPI Registry Number	DRN	Y (5)	N
DWPI Update (formerly Derwent Week)	DW	Y	N
DWPI Update (formerly Derwent Week), first and latest	DUPD	Y	Y
DWPI Update, Basic (formerly Derwent Week)	DW.B	Y	N
Entry Date	ED	Y	Y
European Patent Classification	EPC (ECLA, EPCLA)	Y	N
File Segment	FS	Y	Y

DWPI Invention Level**SELECT, ANALYZE, and SORT Fields (cont'd)**

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Filing Details	FDT	Y (5)	N
Filing Details, Patent Country	FDT.PC (RLPC)	Y (5)	N
Filing Details, Patent Kind	FDT.PK (RLPK)	Y (5)	N
Filing Details, Patent Number	FDT.PN (RLPN)	Y (5)	N
Filing Details, Type	FDT.TP	Y	N
ICO (in-computer-only) Classification	ICO	Y	N
Index term	IT (KW)	Y (5)	N
International Patent Classification (ICM, ICS, ICA, ICI, IPCI, IPCR)	IPC	Y	N
Inventor	IN (AU)	Y	Y
IPC, Additional (supplementary, IPC 1-7)	ICA	Y	N
IPC, Index (complementary, IPC 1-7)	ICI	Y	N
IPC, Main (IPC 1-7)	ICM	Y	Y
IPC, Main and Secondary (IPC 1-7)	IC	Y	N
IPC, Main or First	IPC.F	Y (6)	Y
IPC, Secondary (IPC 1-7)	ICS	Y	N
Japanese Patent Classification (FI-Terms)	FCL (JPC)	Y (5)	N
Japanese Patent Classification (FI-Terms, additional)	FACL	Y (5)	N
Japanese Patent Classification (FI-Terms, index)	FICL	Y (5)	N
Japanese Patent Classification (FI-Terms, main)	FMCL	Y (5)	Y
Japanese Patent Classification (FI-Terms, secondary)	FSCL	Y (5)	N
Japanese Patent Classification (F-Terms)	FTRM (FTERM, FTCLA, JPCLA)	Y	N
Language	LA	Y	N
Manual Code	MC	Y	N
Markush Compound Number	MCN	Y (5)	N
Markush Compound Number, with Role	MCN.WR	Y (5)	N
Patent Assignee	PA	Y	Y
Patent Assignee Code	PACO	Y	Y
Patent Assignee Code and Name	PAX	Y (5)	N
Patent Countries	PCS	Y (7,5)	N
Patent Country	PC	Y (5)	N
Patent Country, Basic	PC.B	Y (5)	Y
Patent Date	PD	Y (5)	N
Patent Date, Basic	PD.B	Y (5)	Y
Patent Information	PN (PI)	Y (5,8)	N
Patent Information, Basic	PN.B	Y (5,9)	Y
Patent Kind Code	PK	Y (5)	N
Patent Kind Code, Basic	PK.B	Y (5)	Y
Patent Number Count	PNC	Y	Y
Patent Number Group (PN, FDT.PN)	PATS	Y (5,10)	N
Patent Number/Kind Code	PNK	Y (5)	N
Patent Number/Kind Code, Basic	PNK.B	Y (5)	N
Priority Country	PRC	Y	N
Priority Country First	PRCF	Y (5)	N
Priority Country, Basic	PRC.B	Y (5)	N
Priority Date	PRD	Y (5)	Y
Priority Date First	PRDF	Y (5)	Y
Priority Date, Basic	PRD.B	Y (5)	N
Priority Number	PRN (PRAI)	Y (11)	N
Priority Number First	PRNF	Y (5)	N
Priority Number, Basic	PRN.B	Y (5)	N
Priority Number, Year	PRN.YR	Y	N

DWPI Invention Level

SELECT, ANALYZE, and SORT Fields (cont'd)

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Priority Year	PRY	Y (5)	Y
Priority Year First	PRYF	Y (5)	Y
Priority Year, Basic	PRY.B	Y (5)	N
Publication Year	PY	Y (5)	Y
Publication Year, Basic	PY.B	Y (5)	Y
Ring Index Number	RIN	Y	N
Ring Index Number, unlinked	RINU	Y	N
Update Date	UP	Y	Y
Update Date Cooperative Patent Classification	UPCP	N	Y
Update Date Enhanced Title	UPTI	N	Y
Update Date Index Term	UPIT (UPKW)	Y	Y
Update Date International Patent Classification	UPIC	Y	Y
Update Date Inventor	UPIN	Y	Y
Update Date Japanese Patent Classification (F-terms, FI-terms)	UPFT	N	Y
Update Date Manual Code	UPMC	N	Y
Update Date Patent Assignee	UPPA	N	Y
Update Date Patent Family	UPP	Y (5)	Y
Update Date Polymer Indexing	UPA	N	Y
US National Patent Classification Current	NCL	Y	N
US National Patent Classification, Current (main)	NCLM	Y	Y
US National Patent Classification, Current (secondary)	NCLS	Y	N

- (1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g., SEL HIT TI.
- (2) SELECTed, ANALYZed and SORted application, priority and patent numbers are in the format set by the Messenger SET PATENT command, either Derwent or STN.
- (3) Selects or analyzes application and priority numbers and appends /APPS to the terms created by SELECT.
- (4) Selects or analyzes DNC and DNN with /DN appended to the terms created by SELECT.
- (5) SELECT HIT or ANALYZE HIT are not valid with this field.
- (6) Appends /IPC.F to the terms created by SELECT.
- (7) Selects or analyzes patent countries and designated states and appends /PCS to the terms created by SELECT.
- (8) Selects or analyzes patent numbers with /PN appended to the terms created by SELECT.
- (9) Selects or analyzes basic patent numbers with /PN.B appended to the terms created by SELECT.
- (10) Selects or analyzes patent number and filing details and appends /PATs to the terms created by SELECT.
- (11) Selects or analyzes priority numbers with /PRN appended to the terms created by SELECT.

Additional DWPI Individual Patent Publication (often First Level Data) SELECT, ANALYZE, and SORT Fields

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Agent	AG	Y	Y
Agent Address	AGA	Y	N
Agent, City	AG.CTY	Y (2)	N
Agent, Country	AG.CNY	Y (2)	N
Agent, Postal Code	AG.ZIP	Y (2)	N
Agent, State	AG.ST	Y (2)	N
Agent, Total	AG.T	Y	N
Application Information, Clarivate	APTS	Y	N
Inventor Address	INA	Y	N
Inventor, City	IN.CTY	Y (2)	N
Inventor, Country	IN.CNY	Y (2)	N
Inventor, Nationality	IN.NAT	Y	N
Inventor, Original	INO	Y	Y
Inventor, Postal Code	IN.ZIP	Y (2)	N
Inventor, Residence	IN.RES	Y	N
Inventor, State	IN.ST	Y (2)	N
Inventor, Total	IN.T	Y	N
IPC, Initial	IIC	Y	N
IPC, Initial, Additional (supplementary)	IICA	Y	N
IPC, Initial, Index (complementary)	IICI	Y	N
IPC, Initial, Main	IICM	Y	Y
IPC, Initial, Secondary	IICS	Y	N
Patent Assignee Address	PAA	Y	N
Patent Assignee, City	PA.CTY	Y	N
Patent Assignee, Country	PA.CNY	Y	N
Patent Assignee, Limitation	PA.LIM	Y	N
Patent Assignee, Nationality	PA.NAT	Y	N
Patent Assignee, Original	PAO	Y	Y
Patent Assignee, Postal Code	PA.ZIP	Y	N
Patent Assignee, Residence	PA.RES	Y	N
Patent Assignee, State	PA.ST	Y	N
Patent Assignee, Total	PA.T	Y	N
Priority Application Information, Clarivate	PRTS	Y	N
Update Date Agent	UPAG	N	Y
Update Date Author Abstract	UPAA	N	Y
Update Date Author Title	UPAT	N	Y
Update Date Claims	UPCL	N	Y
US National Patent Classification, Issued	INCL	Y	Y
US National Patent Classification, Issued (main)	INCLM	Y	N
US National Patent Classification, Issued (secondary)	INCLS	Y	N

(1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g. SEL HIT INA.

(2) SELECT HIT or ANALYZE HIT are not valid with this field.

Citation Data Fields

SELECT, ANALYZE, and SORT Fields

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Citation Category	CAT	Y	N
Citation Category, Cited	CAT.D	Y	N
Citation Category, Citing	CAT.G	Y	N
Cited Accession Number	AN.D	Y	N
Cited Inventor	IN.D	Y	N
Cited Patent Assignee	PA.D	Y (2)	N
Cited Patent Assignee Code	PACO.D	Y (2)	N
Cited Patent Assignee Code and Name	PAX.D	Y	N
Cited Patent Country	PC.D	Y (2)	N
Cited Patent Date	PD.D	Y (2)	N
Cited Patent Kind Code	PK.D	Y (2)	N
Cited Patent Number	PN.D	Y (2)	N
Cited Patent Year	PY.D	Y (2)	N
Citing Accession Number	AN.G	Y	N
Citing Inventor	IN.G	Y	N
Citing Patent Assignee	PA.G	Y (2)	N
Citing Patent Assignee Code	PACO.G	Y (2)	N
Citing Patent Assignee Code and Name	PAX.G	Y	N
Citing Patent Country	PC.G	Y (2)	N
Citing Patent Date	PD.G	Y (2)	N
Citing Patent Kind Code	PK.G	Y (2)	N
Citing Patent Number	PN.G	Y (2)	N
Citing Patent Year	PY.G	Y (2)	N
Digital Object Identifier	DOI	Y (2)	N
Origin of Citation	ORC	Y	N
Update Date, Cited	UPD	N	Y
Update Date, Citing	UPG	N	Y
XP Document Number	XP	Y	N

(1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g. SEL HIT PA.D.

(2) SELECT HIT or ANALYZE HIT are not valid with this field.

Citation Count Fields

SELECT, ANALYZE, and SORT Fields

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Cited DWPI Accession Number Count	ANC.D	Y	Y
Cited Literature Reference Count	CRC	Y	Y
Cited Patents Count	PNC.D	Y	Y
Cited Patents Country Count	PCC.D	Y	Y
Cited Reference Count (total)	REC	Y	Y
Citing DWPI Accession Number Count	ANC.G	Y	Y
Citing Patents Count	PNC.G	Y	Y
Citing Patents Country Count	PCC.G	Y	Y

(1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g. SEL HIT PNC.G

Sample Records

DISPLAY IFULLLG

L1 ANSWER 1 OF 1 WPIX COPYRIGHT 2024 CLARIVATE on STN
 ACCESSION NUMBER: 2018-08951P [201812] WPIX [Full-text](#)
 CROSS REFERENCE: 2018-08951J; 2018-08951L; 2018-08951M; 2018-08951N;
 2018-08951Q; 2018-08991C; 2018-65567S; 2019-71222S;
 2019-71222T; 2021-08476T; 2022-153370; 2023-315094
 TITLE: Transdermal delivery system for administering donepezil
 base used for treating Alzheimer's disease, comprises
 skin contact adhesive layer, and drug reservoir
 comprising acrylate copolymer, glycerin and donepezil
 base
 DERWENT CLASS: A96; B03; B05; B07
 INVENTOR: JAIN A K; LEE E S; SAGI A; SINGH P
 PATENT ASSIGNEE: (RIUM-C) CORIUM INC; (RIUM-C) CORIUM INT INC; (CORI-N)
 CORIUM INT INC
 COUNTRY COUNT: 135

PATENT INFORMATION:

PATENT NO	KIND	DATE	WEEK	LA	PG

US 20180028462	A1	20180201 (201812)	*	EN	24[5]
AU 2017302306	A1	20190214 (201913)		EN	
CA 3031945	A1	20180201 (201913)		EN	
KR 2019034601	A	20190402 (201927)		KO	
US 10300025	B2	20190528 (201940)		EN	
CN 109789105	A	20190521 (201941)		ZH	
EP 3490541	A2	20190605 (201942)		EN	
JP 2019523268	T	20190822 (201964)		JA	34
KR 2406482	B1	20220608 (2022048)		KO	
KR 2022082928	A	20220617 (2022051)		KO	
JP 2022093707	A	20220623 (2022053)		JA	
JP 2022121629	A	20220819 (2022072)		JA	
JP 7153010	B2	20221013 (2022084)		JA	
CN 109789105	B	20221227 (2023003)		ZH	
JP 2019523270	T	20190822 (2023030)		JA	37
WO 2018022817	A1	20180201 (2023030)		EN	
JP 7251033	B2	20230404 (2023031)		JA	
KR 2022082098	A	20220616 (2023052)		KO	
KR 2545643	B1	20230621 (2023052)		KO	
KR 2545649	B1	20230622 (2023052)		KO	
KR 2023097203	A	20230630 (2023054)		KO	
AU 2017302307	A1	20190214 (2023056)		EN	
AU 2023203616	A1	20230706 (2023056) #		EN	
AU 2023203618	A1	20230706 (2023056) #		EN	
WO 2018022816	A1	20180201 (2023056)		EN	
CN 109789106	A	20190521 (2023057)		ZH	
CN 116270551	A	20230623 (2023057)		ZH	
CN 109789106	B	20230627 (2023057)		ZH	
KR 2022082929	A	20220617 (2023058)		KO	
KR 2555208	B1	20230717 (2023058)		KO	
SG 11201900692	B	20230201 (2023062)		EN	
KR 2023109782	A	20230720 (2023064)		KO	
AU 2023204240	A1	20230727 (2023068) #		EN	
MX 2022006681	A1	20220711 (2023091)		ES	
CN 116966166	A	20231031 (2023093)		ZH	

APPLICATION DETAILS:

PATENT NO	KIND	APPLICATION	DATE
US 20180028462	A1	US 2017-15660939	20170726
US 20180028462	A1 Provisional	US 2017-504408P	20170510
US 20180028462	A1 Provisional	US 2017-504391P	20170510
US 20180028462	A1 Provisional	US 2017-457794P	20170210
US 20180028462	A1 Provisional	US 2017-444763P	20170110
US 20180028462	A1 Provisional	US 2017-444745P	20170110
US 20180028462	A1 Provisional	US 2016-423133P	20161116
US 20180028462	A1 Provisional	US 2016-367542P	20160727
US 20180028462	A1 Provisional	US 2016-367502P	20160727
US 10300025	B2 Provisional	US 2016-367502P	20160727
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AU 2023203618	A1 Div Ex	AU 2017-302306	20170726
AU 2017302307	A1	AU 2017-302307	20170726
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CN 109789105	B	CN 2017-80059417	20170726
CN 116270551	A Div Ex	CN 2017-80059417	20170726
CN 109789106	B	CN 2017-80059437	20170726
CN 109789106	A	CN 2017-80059437	20170726
CN 116966166	A Div Ex	CN 2017-80059437	20170726
EP 3490541	A2	EP 2017-749568	20170726
US 10300025	B2	US 2017-15660939	20170726
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KR 2019034601	A PCT Application	WO 2017-US44048	20170726
CN 109789105	A PCT Application	WO 2017-US44048	20170726
EP 3490541	A2 PCT Application	WO 2017-US44048	20170726
JP 2019523268	T PCT Application	WO 2017-US44048	20170726
KR 2406482	B1 PCT Application	WO 2017-US44048	20170726
KR 2022082928	A PCT Application	WO 2017-US44048	20170726
JP 7153010	B2 PCT Application	WO 2017-US44048	20170726
CN 109789105	B PCT Application	WO 2017-US44048	20170726
KR 2545649	B1 PCT Application	WO 2017-US44048	20170726
AU 2017302307	A1 PCT Application	WO 2017-US44049	20170726
WO 2018022816	A1	WO 2017-US44049	20170726
CN 109789106	B PCT Application	WO 2017-US44049	20170726
CN 109789106	A PCT Application	WO 2017-US44049	20170726
KR 2022082929	A PCT Application	WO 2017-US44049	20170726
KR 2555208	B1 PCT Application	WO 2017-US44049	20170726
KR 2023109782	A PCT Application	WO 2017-US44049	20170726
WO 2018022817	A1	WO 2017-US44050	20170726
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JP 7251033	B2 PCT Application	WO 2017-US44050	20170726
KR 2545643	B1 PCT Application	WO 2017-US44050	20170726
KR 2022082098	A PCT Application	WO 2017-US44050	20170726
KR 2023097203	A PCT Application	WO 2017-US44050	20170726
SG 11201900692	B PCT Application	WO 2017-US44050	20170726

WPIDS / WPINDEX / WPIX

CA 3031945 A1 PCT Nat. Entry	CA 2017-3031945 20190124
CN 109789105 A PCT Nat. Entry	CN 2017-80059417 20190326
CN 109789105 B PCT Nat. Entry	CN 2017-80059417 20190326
CN 109789106 B PCT Nat. Entry	CN 2017-80059437 20190326
CN 109789106 A PCT Nat. Entry	CN 2017-80059437 20190326
JP 2019523268 T	JP 2019-503974 20170726
JP 7153010 B2	JP 2019-503974 20170726
JP 2022093707 A Div Ex	JP 2019-504000 20170726
JP 2022121629 A Div Ex	JP 2019-504001 20170726
JP 2019523270 T	JP 2019-504001 20170726
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KR 2545643 B1 Div Ex	KR 2019-7005331 20170726
KR 2022082098 A Div Ex	KR 2019-7005331 20170726
KR 2019034601 A	KR 2019-7005737 20170726
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KR 2545649 B1 Div Ex	KR 2019-7005737 20170726
KR 2022082929 A Div Ex	KR 2019-7005739 20170726
KR 2555208 B1 Div Ex	KR 2019-7005739 20170726
SG 11201900692 B	SG 2019-11201900692 20170726
SG 11201900692 B PCT Nat. Entry	SG 2019-11201900692 20190125
KR 2406482 B1 PCT Nat. Entry	KR 2019-7005737 20190226
CN 116270551 A	CN 2022-11676624 20170726
KR 2022082928 A	KR 2022-7018732 20170726
KR 2545649 B1	KR 2022-7018732 20170726
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KR 2023097203 A Div Ex	KR 2022-7018749 20170726
SG 11201900692 B Related to	SG 2022-10202260454 20170726
MX 2022006681 A1	MX 2022-6681 20190125
JP 2022093707 A	JP 2022-76575 20220506
KR 2022082928 A PCT Nat. Entry	KR 2022-7018732 20220602
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CN 116966166 A	CN 2023-10658352 20170726
KR 2023097203 A	KR 2023-7020235 20170726
KR 2023109782 A	KR 2023-7023326 20170726
AU 2023203616 A1	AU 2023-203616 20230609
AU 2023203618 A1	AU 2023-203618 20230609
KR 2023097203 A PCT Nat. Entry	KR 2023-7020235 20230615
AU 2023204240 A1	AU 2023-204240 20230703
KR 2023109782 A PCT Nat. Entry	KR 2023-7023326 20230710

FILING DETAILS:

PATENT NO	KIND	PATENT NO
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CN 109789105 B	Previous Publ	CN 109789105 A
CN 109789106 B	Previous Publ	CN 109789106 A
JP 7153010 B2	Previous Publ	JP 2019523268 T
JP 7251033 B2	Previous Publ	JP 2019523270 T
US 10300025 B2	Previous Publ	US 2018028462 A

CA 3031945 A1	Based on	WO 2018022815 A
AU 2017302306 A1	Based on	WO 2018022815 A
KR 2019034601 A	Based on	WO 2018022815 A
CN 109789105 A	Based on	WO 2018022815 A
EP 3490541 A2	Based on	WO 2018022815 A
JP 2019523268 T	Based on	WO 2018022815 A
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KR 2545649 B1	Based on	WO 2018022815 A
AU 2017302307 A1	Based on	WO 2018022816 A
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CN 109789106 A	Based on	WO 2018022816 A
KR 2022082929 A	Based on	WO 2018022816 A
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KR 2023109782 A	Based on	WO 2018022816 A
JP 2019523270 T	Based on	WO 2018022817 A
JP 7251033 B2	Based on	WO 2018022817 A
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KR 2023097203 A	Based on	WO 2018022817 A
SG 11201900692 B	Based on	WO 2018022817 A

PRIORITY APPLN. INFO:	US 2017-15660939	20170726
	US 2017-504391P	20170510
	US 2017-504408P	20170510
	US 2017-457794P	20170210
	US 2017-444745P	20170110
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	AU 2023-203616	20230609
	AU 2023-203618	20230609
	AU 2023-204240	20230703

INT. PATENT CLASSIF.:

IPC RECLASSIF.: A61K0031-00 [I,A]; A61K0031-045 [N,A]; A61K0031-13 [I,A];
 A61K0031-137 [I,A]; A61K0031-18 [I,A]; A61K0031-19 [I,A];
 A61K0031-192 [I,A]; A61K0031-196 [I,A]; A61K0031-27 [I,A];
 ; A61K0031-445 [I,A]; A61K0031-663 [I,A]; A61K0047-02
 [I,A]; A61K0047-10 [I,A]; A61K0047-12 [I,A]; A61K0047-14
 [I,A]; A61K0047-20 [I,A]; A61K0047-26 [I,A]; A61K0047-32
 [I,A]; A61K0009-70 [I,A]; A61P0013-00 [I,A]; A61P0013-02
 [I,A]; A61P0013-08 [I,A]; A61P0025-00 [I,A]; A61P0025-04
 [I,A]; A61P0025-14 [I,A]; A61P0025-16 [I,A]; A61P0025-22
 [I,A]; A61P0025-24 [I,A]; A61P0025-26 [I,A]; A61P0025-28
 [I,A]; A61P0025-36 [I,A]; A61P0035-00 [I,A]; C08K0005-00
 [I,A]

CPC: A61K0031-00; A61K0031-045; A61K0031-13; A61K0031-137;
 A61K0031-18; A61K0031-192; A61K0031-196; A61K0031-216;
 A61K0031-27; A61K0031-381; A61K0031-4045; A61K0031-439;
 A61K0031-445; A61K0031-4458; A61K0031-4468; A61K0047-02;
 A61K0047-10; A61K0047-12; A61K0047-14; A61K0047-20;
 A61K0047-32; A61K0009-7023; A61K0009-7038; A61K0009-7046;
 A61K0009-7053; A61K0009-7061; A61K0009-7061;
 A61K0009-7084; A61K0009-7084; A61K0009-7092; A61P0013-00;
 A61P0013-02; A61P0013-08; A61P0025-00; A61P0025-02;

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A61P0025-04; A61P0025-14; A61P0025-16; A61P0025-22;
 A61P0025-24; A61P0025-26; A61P0025-28; A61P0025-36;
 A61P0029-00; A61P0035-00; C08K0005-0016

USCLASS NCLM:

JAP. PATENT CLASSIF.:

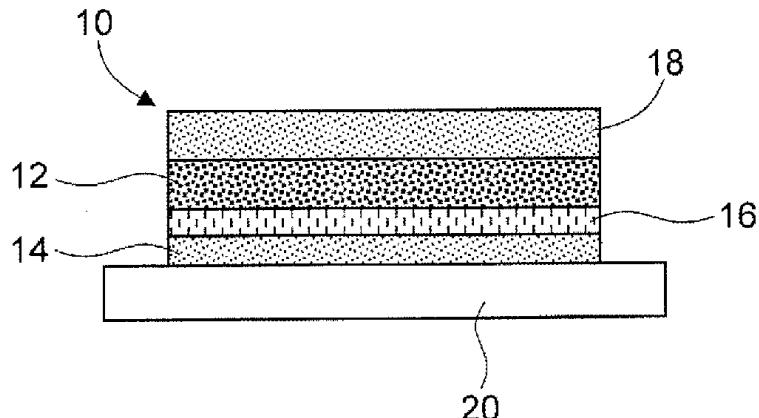
MAIN: A61K0009-70 401

SECONDARY: A61K0031-13; A61K0031-137; A61K0031-18; A61K0031-19;
 A61K0031-192; A61K0031-196; A61K0031-27; A61K0031-445;
 A61K0031-663; A61K0047-02; A61K0047-10; A61K0047-14;
 A61K0047-20; A61K0047-26; A61K0047-32; A61P0013-00;
 A61P0013-08; A61P0025-14; A61P0025-16; A61P0025-22;
 A61P0025-24; A61P0025-26; A61P0025-28; A61P0025-36

FTERM CLASSIF.:

4C076; 4C086; 4C206; 4C086/AA01; 4C206/AA01; 4C086/AA02;
 4C206/AA02; 4C076/AA72; 4C076/AA81; 4C076/BB31;
 4C086/BC21; 4C076/CC01; 4C086/DA02; 4C206/DA22;
 4C206/DA25; 4C206/DA30; 4C086/DA34; 4C076/DD37;
 4C076/DD38; 4C076/DD44; 4C076/DD47; 4C076/DD48;
 4C076/DD55; 4C076/EE03; 4C076/EE13; 4C076/EE27;
 4C076/EE49; 4C206/FA10; 4C206/FA29; 4C206/FA31;
 4C076/FF68; 4C206/HA24; 4C206/JA13; 4C206/KA01;
 4C206/KA04; 4C206/KA09; 4C086/MA01; 4C206/MA01;
 4C086/MA05; 4C086/MA63; 4C206/MA83; 4C086/NA14;
 4C086/ZA01; 4C206/ZA01; 4C086/ZA11; 4C206/ZA11;
 4C086/ZA12; 4C206/ZA12; 4C086/ZA16; 4C206/ZA16;
 4C086/ZA81; 4C206/ZA81

GRAPHIC IMAGE:

**BASIC ABSTRACT:**

US 20180028462 A1 UPAB 20180222

NOVELTY - A transdermal delivery system comprises a skin contact adhesive layer (14) for attaching to skin of user, and a drug reservoir (12) comprising acrylate copolymer, glycerin and donepezil base generated in-situ by reaction of donepezil hydrochloride and alkaline salt.

DETAILED DESCRIPTION - INDEPENDENT CLAIMS are included for a composition comprising drug reservoir which contains donepezil base, glycerin, and acrylic acid/vinyl acetate copolymer; or drug reservoir which contains donepezil base, solvent comprising triethyl citrate, lauryl lactate, sorbitan monolaurate and/or glycerin, and crosslinked polyvinylpyrrolidone and acrylic acid/vinyl acetate copolymer.

ACTIVITY - Neuroprotective; Nootropic. Test details are described but no results given.

MECHANISM OF ACTION - Acetylcholinesterase Inhibitor.

USE - Transdermal delivery system for administering donepezil base used for treating Alzheimer's disease in subject (claimed).

ADVANTAGE - The system achieves transdermal delivery of therapeutic agent at steady state that is bioequivalent to oral administration of therapeutic agent.

DESCRIPTION OF DRAWINGS - The drawing shows a sectional view of transdermal delivery system.

- Drug reservoir (12)
- Skin contact adhesive layer (14)
- Microporous membrane (16)
- Backing layer (18)
- Release liner (20)

TECHNOLOGY FOCUS:

INORGANIC CHEMISTRY - Preferred Components: The alkaline salt in the drug reservoir layer is sodium carbonate, potassium carbonate, trisodium phosphate, disodium hydrogen phosphate, or preferably sodium bicarbonate.

ORGANIC CHEMISTRY - Preferred Components: The intermediate layer is a microporous membrane (16). The pores in microporous membrane contain solvent composition comprising triethyl citrate, sorbitan monolaurate, and/or lauryl lactate. The drug reservoir layer further comprises triethyl citrate and sorbitan monolaurate and/or lauryl lactate. The alkaline salt may be sodium oxalate, sodium succinate, sodium citrate, and sodium salicylate.

PHARMACEUTICALS - Preferred Components: The delivery system further comprises an intermediate layer disposed between contact adhesive layer and drug reservoir, a first backing layer in contact with the drug reservoir layer, an adhesive overlay in contact with the first backing layer, and a second backing layer in contact with the adhesive overlay. The drug reservoir comprises donepezil base generated in situ by reaction of 5-25 weight%, preferably 10-18 weight% donepezil hydrochloride and 1-5 weight% sodium bicarbonate; 0-15 weight%, preferably 8-12 weight% triethyl citrate; 0-5 weight%, preferably 1.5-2.5 weight% sorbitan monolaurate; 5-15 weight%, preferably 9-11 weight% glycerin; 1-10 weight% lauryl lactate; 5-25 weight%, preferably 13-17 weight% crosslinked polyvinylpyrrolidone; and 30-65 weight%, preferably 40-42 weight% acrylate-vinyl acetate copolymer.

POLYMERS - Preferred Components: The skin contact adhesive layer comprises acrylic acid/vinyl acetate copolymer, crosslinked polyvinylpyrrolidone, and solvent composition. The skin contact adhesive layer is manufactured from adhesive formulation that does not contain donepezil base or donepezil salt. The microporous membrane is polypropylene membrane. The adhesive overlay is a single layer of acrylate copolymer or comprises a first layer comprising polyisobutylene and polybutene, and a second layer comprising acrylic adhesive.

EXTENSION ABSTRACT:

ADMINISTRATION - The transdermal delivery system is administered once weekly and provides donepezil base at 1-25 mg/24 hours (claimed).

EXAMPLE - 1.20 g Sorbitan monolaurate was dissolved in 6 g triethyl citrate and mixed with 1.80 g lauryl lactate and 89.69 g ethyl acetate. 6 g Glycerin was added and mixed. 9 g Donepezil hydrochloride and 1.82 g sodium bicarbonate were added and dispersed in the mixture. 12 g Crosslinked micronized polyvinylpyrrolidone was added and the mixture was homogenized. 43.93 g Acrylic acid/vinyl acetate copolymer was added and mixed. The wet adhesive formulation was coated on release liner and dried to yield dry coating weight of 12 mg/cm² to obtain drug reservoir. 0.60 g Sorbitan monolaurate was dissolved in 3 g triethyl citrate and mixed with 0.9 g lauryl lactate, 25.45 g ethyl acetate and 1.34 g isopropanol. 6 g Crosslinked, micronized polyvinylpyrrolidone was added and the mixture was homogenized. 38.61 g Acrylic acid/vinyl acetate copolymer was added and mixed. The wet adhesive formulation was coated on a release liner and dried to obtain dry coating weight of 5 mg/cm² to obtain contact adhesive. A rate controlling membrane was laminated on adhesive side of

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drug reservoir. The contact adhesive was laminated on top of rate controlling membrane. The release liner on drug reservoir side was replaced and laminated with backing film. The final five layer laminate was die-cut into transdermal patches.

FILE SEGMENT: CPI

MANUAL CODE: CPI: A04-D05A; A04-F04B; A04-F06E5; A04-F09; A12-V01; B04-C03; B05-A01A; B05-A01B; B05-B02A3; B07-A02A; B07-D05; B10-C02; B10-C03; B10-E04C; B10-G02; B12-M02D; B12-M02F; B14-D07A; B14-J01A4

DISPLAY MEMB

Member(0001)

PI US 20180028462 A1 20180201 (201812) * EN 24[5]

TIEN DONEPEZIL TRANSDERMAL DELIVERY SYSTEM

IN LEE E S

INO: Lee, Eun Soo

INA: Redwood City, CA, US

JAIN A K

INO: Jain, Amit K.

INA: Milpitas, CA, US

SINGH P

INO: Singh, Parminder

INA: Union City, CA, US

PA (CORI-N) CORIUM INT INC

PAO: CORIUM INTERNATIONAL, INC.

PAA: Menlo Park, CA, US

Residence: US

Nationality: US

ADT US 20180028462 A1 US 2017-15660939 20170726; US 20180028462 A1 Provisional US 2017-504408P 20170510; US 20180028462 A1 Provisional US 2017-504391P 20170510; US 20180028462 A1 Provisional US 2017-457794P 20170210; US 20180028462 A1 Provisional US 2017-444763P 20170110; US 20180028462 A1 Provisional US 2017-444745P 20170110; US 20180028462 A1 Provisional US 2016-423133P 20161116; US 20180028462 A1 Provisional US 2016-367542P 20160727; US 20180028462 A1 Provisional US 2016-367502P 20160727

APTS 2017US-000660939 20170726; 2017US-000504408P 20170510; 2017US-000504391P 20170510; 2017US-000457794P 20170210; 2017US-000444763P 20170110; 2017US-000444745P 20170110; 2016US-000423133P 20161116; 2016US-000367542P 20160727; 2016US-000367502P 20160727

IPCI Current: A61K0009-70 [I,A]

Original: A61K0009-70 [I,A]

CPC Current: A61K0031-00; A61K0031-045; A61K0031-13; A61K0031-137; A61K0031-18; A61K0031-27; A61K0031-445; A61K0047-02; A61K0047-10; A61K0047-12; A61K0047-32; A61K0009-7023; A61K0009-7038; A61K0009-7053; A61K0009-7061; A61K0009-7084; A61K0009-7092; C08K0005-0016
Original: A61K0031-445; A61K0009-7038; A61K0009-7084

NCL NCLM 001/001.000

ABEN A transdermal delivery system for systemic delivery of donepezil is described, where the system comprises an adhesive matrix drug reservoir layer comprised of a copolymer of acrylic acid/vinyl acetate, triethyl citrate, and donepezil base generated in situ by reaction of donepezil HCl and an alkaline salt. The system is provided for treatment of Alzheimer's disease, and achieves transdermal delivery of the therapeutic agent at steady state that is bioequivalent to administration of the therapeutic agent orally.

CLMEN [CLAIM 1] 1. A transdermal delivery system for systemic delivery of donepezil, comprising: a skin contact adhesive layer to attach the system to the skin of a user, and a drug reservoir comprised of (i) an acrylate copolymer, (ii) glycerin, and (iii) donepezil base generated in situ by

reaction of donepezil HCl and an alkaline salt.

[CLAIM 2] 2. The system of claim 1, further comprising an intermediate layer directly on the contact adhesive layer and disposed between the contact adhesive layer and the drug reservoir.

[CLAIM 3] 3. The system of claim 2, wherein the intermediate layer is a microporous membrane comprising a plurality of pores.

[CLAIM 4] 4. The system of claim 3, wherein the plurality of pores in the microporous membrane contains a solvent composition comprised of one or more of triethyl citrate, sorbitan monolaurate, and lauryl lactate.

[CLAIM 5] 5. The system of claim 1, wherein the skin contact adhesive layer is comprised of a copolymer of acrylic acid/vinyl acetate.

[CLAIM 6] 6. The system of claim 5, wherein the skin contact adhesive layer additionally comprises crosslinked polyvinylpyrrolidone.

[CLAIM 7] 7. The system of claim 1, wherein the skin contact adhesive layer comprises a solvent composition comprising one or more solvents selected from the group consisting of triethyl citrate, sorbitan monolaurate, and lauryl lactate.

[CLAIM 8] 8. The system of claim 1, wherein the skin contact adhesive layer is manufactured from an adhesive formulation that does not comprise donepezil base or a donepezil salt.

[CLAIM 9] 9. The system of claim 1, wherein the alkaline salt in the drug reservoir layer is sodium bicarbonate.

[CLAIM 10] 10. The system of claim 1, the drug reservoir layer additionally comprises triethyl citrate.

[CLAIM 11] 11. The system of claim 10, wherein the drug reservoir layer additionally comprises one or both of sorbitan monolaurate and lauryl lactate.

[CLAIM 12] 12. The system of claim 1, further comprising a first backing layer in contact with the drug reservoir layer, an adhesive overlay in contact with the first backing layer; and a second backing layer in contact with the adhesive overlay.

[CLAIM 13] 13. The system of claim 12, wherein the adhesive overlay is single layer comprised of an acrylate copolymer.

[CLAIM 14] 14. The system of claim 13, wherein the adhesive overlayer is comprised of a first layer and a second layer, the first layer composed of a polyisobutylene and polybutene and the second layer composed of an acrylic adhesive.

[CLAIM 15] 15. A composition, comprising:a drug reservoir comprising (i) donepezil base generated in situ by reaction of donepezil HCl and an alkaline salt; (ii) glycerine; and (iii) a copolymer of acrylic acid/vinyl acetate.

[CLAIM 16] 16. The composition of claim 15, wherein the drug reservoir further comprises triethyl citrate or sorbitan monolaurate.

[CLAIM 17] 17. The composition of claim 15, wherein the drug reservoir comprises an acrylic acid/vinyl acetate copolymer adhesive and a crosslinked polyvinylpyrrolidone.

[CLAIM 18] 18. The composition of claim 15, wherein the alkaline salt is selected from the group consisting of sodium carbonate, sodium bicarbonate, potassium carbonate, potassium bicarbonate, trisodium phosphate, disodium hydrogen phosphate, sodium oxybate, sodium succinate, sodium citrate, and sodium salicylate.

[CLAIM 19] 19. A composition, comprising:a drug reservoir consisting essentially of donepezil base generated in situ by reaction of donepezil HCl and sodium bicarbonate; a solvent composition comprising one or more of triethyl citrate, lauryl lactate, sorbitan monolaurate, and glycerin; crosslinked polyvinylpyrrolidone and a copolymer of acrylic acid/vinyl acetate.

[CLAIM 20] 20. A composition, comprising:a drug reservoir consisting essentially of:(a) donepezil base generated in situ by reaction of between about 5-25 wt % donepezil HCl and between about 1-5 wt % sodium bicarbonate;(b) about 0-15 wt % triethyl citrate;(c) about 0-5 wt %

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sorbitan monolaurate(d) about 5-15 wt % glycerin;(e) about 1-10 wt % lauryl lactate;(f) about 5-25 wt % crosslinked polyvinylpyrrolidone; and(g) about 30-65 wt % acrylate-vinylacetate copolymer.

[CLAIM 21] 21. A composition, comprising:a drug reservoir consisting essentially of:(a) donepezil base generated in situ by reaction of between about 10-18 wt % donepezil HCl and between about 1-5 wt % sodium bicarbonate;(b) about 8-12 wt % triethyl citrate;(c) about 1.5-2.5 wt % sorbitan monolaurate(d) about 9-11 wt % glycerin;(e) about 1-10 wt % lauryl lactate;(f) about 13-17 wt % crosslinked polyvinylpyrrolidone; and(g) about 40-42 wt % acrylate-vinylacetate copolymer.

[CLAIM 22] 22. A composition, comprising:(a) a drug reservoir comprised of the composition of claim 15;(b) a microporous membrane or a non-woven layer; and(c) a skin contact adhesive.

[CLAIM 23] 23. The composition according to claim 22, wherein the microporous membrane is a polypropylene membrane.

[CLAIM 24] 24. The composition of claim 22, wherein the composition comprises a microporous membrane with a plurality of pores, the plurality of pores contain a solvent composition comprised of one or more of triethyl citrate, sorbitan monolaurate, and lauryl lactate.

[CLAIM 25] 25. A method for delivering donepezil base to a subject, comprising:providing a transdermal delivery system according to claim 1, andadministering or instructing to administer the transdermal delivery system to the skin of a subject.

[CLAIM 26] 26. The method of claim 25, wherein the method is for treatment of a subject with Alzheimer's disease.

[CLAIM 27] 27. The method of claim 26, wherein the administering or instructing to administer comprises administering or instructing to administer once weekly.

[CLAIM 28] 28. The method of claim 25, wherein the transdermal delivery system comprises a dose of donepezil base to provide between 1-25 mg/24 hours.

Member(0002)

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DISPLAY CITN (full citation information)

AN 2018-58265Y [201854] WPIX

Citation Counters

PNC.D	23	Cited Patents Count
PCC.D	3	Cited Patents Country Count
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REC	39	Cited Reference Count (total)
ANC.D	23	Cited DWPI Accession Number Count
PNC.G	3	Citing Patents Count
PCC.G	2	Citing Patents Country Count
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EXF Examiner's Field of Search

Citing Publication EXF Examiner's Field of Search

US 10898617 B2	CPC	A61L2300-404; A61L2300-42; A61L2400-18; A61L2420-02; A61L0029-041; A61L0029-043; A61L0029-06; A61L0029-16; A61L0031-042; A61L0031-046; A61L0031-06; A61L0031-16
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Citing Publication	By	Cat	Cited Patent	Date	Accession Number
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			PA: (GREE-I) GREENWALD H J; (WANG-I) WANG X		
			IN: GREENWALD H J; WANG X		
			Relevant passages: [0059]		
			Relevant to claim: 5		
	E	X	US 20120136323 A1	20120531	2011-B93445
			PA: (NOVA-N) NOVAN INC		
			IN: BAUMAN S; JOSHI P R; STASKO N		
			Relevant passages: abstract Fig. 1, [0117], [0137]		
			[0059] claim 3 F.2d [0063] and [0064]		
			[0081] [0079]-[0080] [0088] claim 9 [0125]		
			claim 13 claim 14 [0145] claim 24 claim		
			15 [0100] and [0113] claim 19 [0147] [0155]		
			claim 22 [0058], [0059], [0063] [0064] para		
			[0058] claim 5 claim 1 Fig. 4B Fig 5B [0138]		
			[0141] column 4 lines 47-51 column 5 lines		
			7-10 claim 18 , abstract Fig. 1, [0117], [0137]		
			[0059] claim 3 F.2d [0063] and [0064]		
			[0081] [0079]-[0080] [0088] claim 9 [0125]		
			claim 13 claim 14 [0145] claim 24 claim		
			15 [0100] and [0113] claim 19 [0147] [0155]		
			claim 22 [0058], [0059], [0063] [0064] para		
			[0058] claim 5 claim 1 Fig. 4B Fig 5B [0138]		
			[0141] column 4 lines 47-51 column 5 lines		
			7-10 claim 18		
			Relevant to claim: 1-4, 6-15, 19, 22, 5, 16-18		
	E	Y	US 7750201 B2	20100706	2008-E59466
			PA: (COVI-C) TYCO HEALTHCARE GROUP LP		
			IN: DOWD B; FINK E D; HEAGLE D G; MULLIGAN S A; ORR S;		
			PATEL H A; SHAH C B; SWANIKER H P; TRANCHEMONTAGNE		

A; VITARIS R F; WARD K

Relevant passages: abstract Fig. 2 | column 5 line 53
 column 6 line 5 | column 4 lines 47-51 | column 5
 lines 7-10 | claim 18 | claim 19 | [0059]

Relevant to claim: 16-18

WO 2018136845 A1 E Y RU 2350356 C1 20090327 2009-G41921
 PA: (CHAS-I) CHASHCHIN V A; (KHOT-I) KHOTIMSKII D V;
 (MANA-I) MANAEVA T V; (VISH-I) VISHNYAKOV A V
 IN: CHASHCHIN V A; KHOTIMSKII D V; MANAEVA T V;
 VISHNYAKOV A V

Relevant passages: , abstract, pp.5-6, examples

Relevant to claim: 21

E Y US 20050107870 A1 20050519 2005-402993
 PA: (GREE-I) GREENWALD H J; (WANG-I) WANG X
 IN: GREENWALD H J; WANG X

Relevant passages: , paragraphs [0274], [0282], [0298]

Relevant to claim: 11, 16-18

E A US 20150297782 A1 20151022 2010-E89227
 PA: (MILL-I) MILLER C; (MURR-I) MURRAY B
 IN: MILLER C; MURRAY B

Relevant to claim: 1-21

EP 3570927 A4 E X US 20110244001 A1 20111006 2011-M58027
 PA: (UYSR-C) UNIV SYRACUSE
 IN: ISHIDA K; MATHER P; ONYEJEWKE I

Relevant passages: claim 1, 5 ; fig. 1, 4, 6 ; para 09,
 35, 28, 70

Relevant to claim: 1-5, 7, 14

E IX WO 2006084912 A1 20060817 2006-578124
 PA: (NOLA-N) NOLABS AB
 IN: PETERS T; PETERS, Tor

Relevant passages: claim 1 ; fig. 1B ; pp. 14, line 26,
 pp. 15, line 15 ; pp. 21, line 15-28

Relevant to claim: 1-5, 7, 10, 14|12, 13, 15

E X WO 2016201237 A1 20161215 2016-77058H
 PA: (UNMI-C) UNIV MICHIGAN
 IN: LAUTNER G; MEYERHOFF M E; SCHWENDEMAN S P

Relevant passages: claim 1, 2, 5, 16 ; fig. 1, 4 ; para
 42, 43 ; para 50, 56 ; pp. 29

Relevant to claim: 1, 4, 5, 8-11, 14

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	E	Y	HARVEY A. LIU ET AL.: "Novel Delivery System for the Bioregulatory Agent Nitric Oxide", CHEMISTRY OF MATERIALS, vol. 21, no. 21, November 2009 (2009-11-01), pages 5032 - 5041,

XP055519461, relevantClaims[14, 21], relevantPassages[], especially p.5034, col. 1]

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EP 3570927 A4 E X ELIZABETH J. BRISBOIS ET AL: "Improved Hemocompatibility of Multilumen Catheters via Nitric Oxide (NO) Release from S -Nitroso- N -acetylpenicillamine (SNAP) Composite Filled Lumen", ACS APPLIED MATERIALS & INTERFACES, vol. 8, no. 43, 21 October 2016 (2016-10-21), US, pages 29270 - 29279, XP055748916, ISSN: 1944-8244, DOI: 10.1021/acsami.6b08707, relevantClaims[1,4-6,8, 14], relevantPassages[pp. 29271, col. 1, |fig. 1, 3, |pp. 29273, para 3.1,]
DOI: <https://doi.org/10.1021/acsami.6b08707>

E See also references of WO 2018136845A1

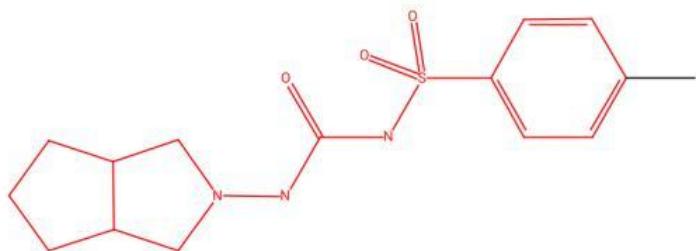
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CGP Citing Patents

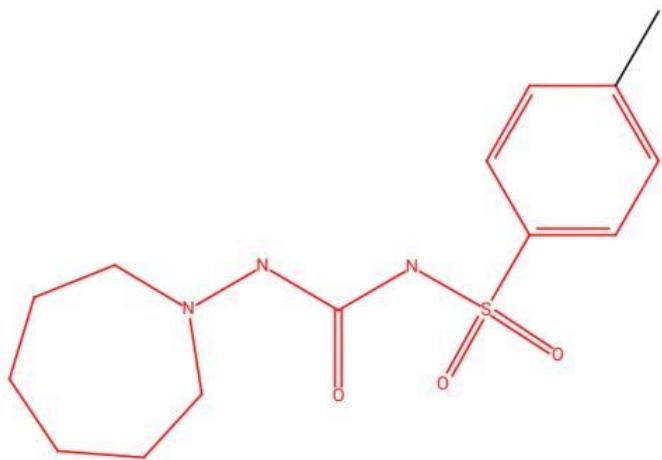
Cited Publication	By	Cat	Citing Patent	Date	Accession Number
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	PA:	(UYSJ-C) UNIV SOUTHWEST JIAOTONG			
	IN:	HE J; TANG P; YANG H; ZHENG X			
	E	XY	WO 2021040813 A1	20210304	2021-195944
	PA:	(NOTA-N) NOTA LAB LLC			
	IN:	KAHN M; MARTIN G; MEYERHOFF M E			
	E	Y	WO 2021040814 A1	20210304	2021-195944
	PA:	(NOTA-N) NOTA LAB LLC			
	IN:	KAHN M; MARTIN G; MEYERHOFF M E			

WPIDS / WPINDEX / WPIX**DISPLAY HITSTR after structure search in DCR and crossover to DWPI**

AN.S DCR-96154
 CN.P GLICLAZIDE
 MF C15 H21 N3 O3 S
 STR



AN.S DCR-109127
 CN.P TOLAZAMIDE
 MF C14 H21 N3 O3 S
 STR

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